



UNITED NATIONS EDUCATIONAL, SCIENTIFIC AND CULTURAL ORGANIZATION
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INTERNATIONAL CENTRE FOR THEORETICAL PHYSICS
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**SCHOOL ON THE USE OF SYNCHROTRON RADIATION
IN SCIENCE AND TECHNOLOGY:
*"John Fuggle Memorial"***

3 November - 5 December 1997

Miramare - Trieste, Italy

**BRAGG-FRESNEL OPTICS
*Principles and Applications***

**Werner Jark
Area di Ricerca
Sincrotrone Trieste, Italy**

BRAGG-FRESNEL OPTICS

Principles and Applications

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PLAN

- **Bragg-Fresnel Optics Principles**
from Zone Plate to Bragg Fresnel Lens
 - **Experimental Results for 1D focussing optics**
 - **Experimental Results for 2D focussing optics**
 - **Applications**
Imaging
- Hard X-RAY Microprobe (LURE- ESRF)**
- **Conclusion**



BRAGG-FRESNEL LENSES

Association of 2 kinds of MICROSTRUCTURE

Multilayer
Crystal

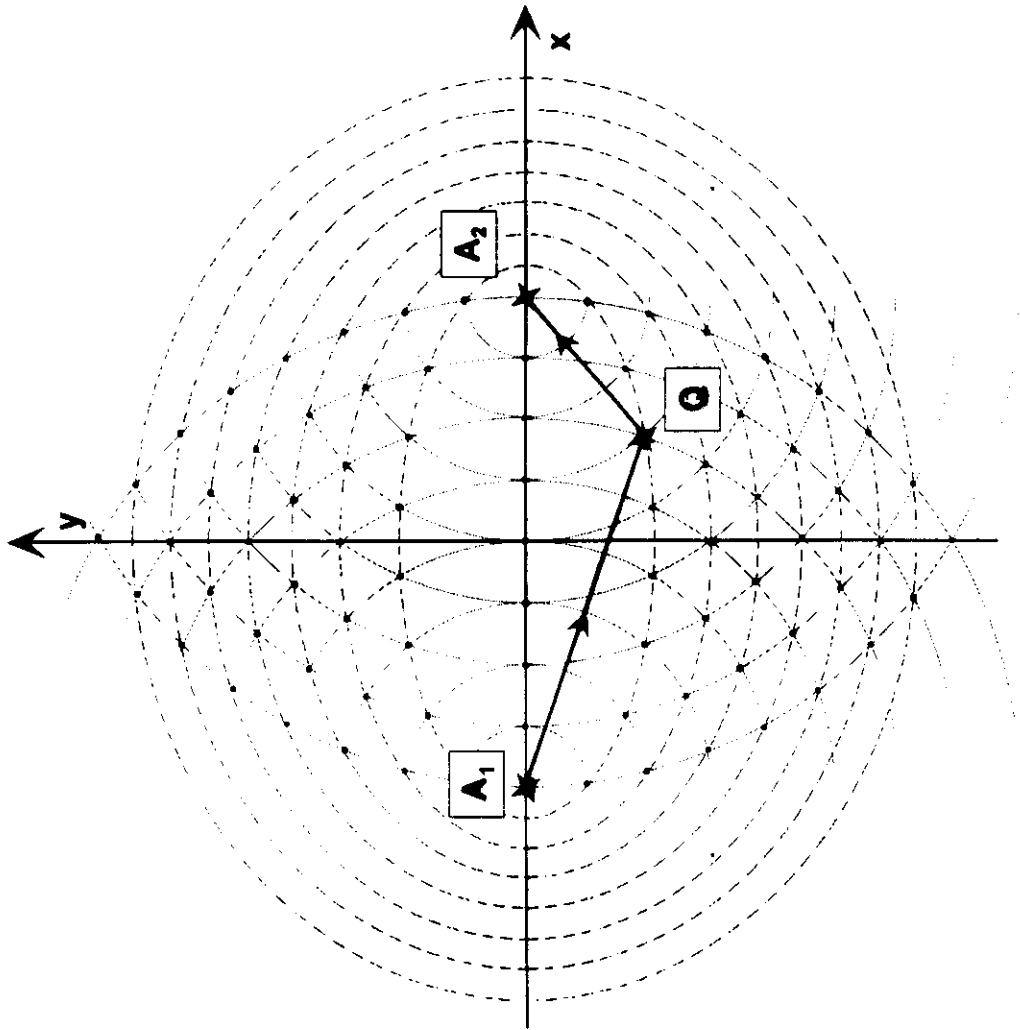


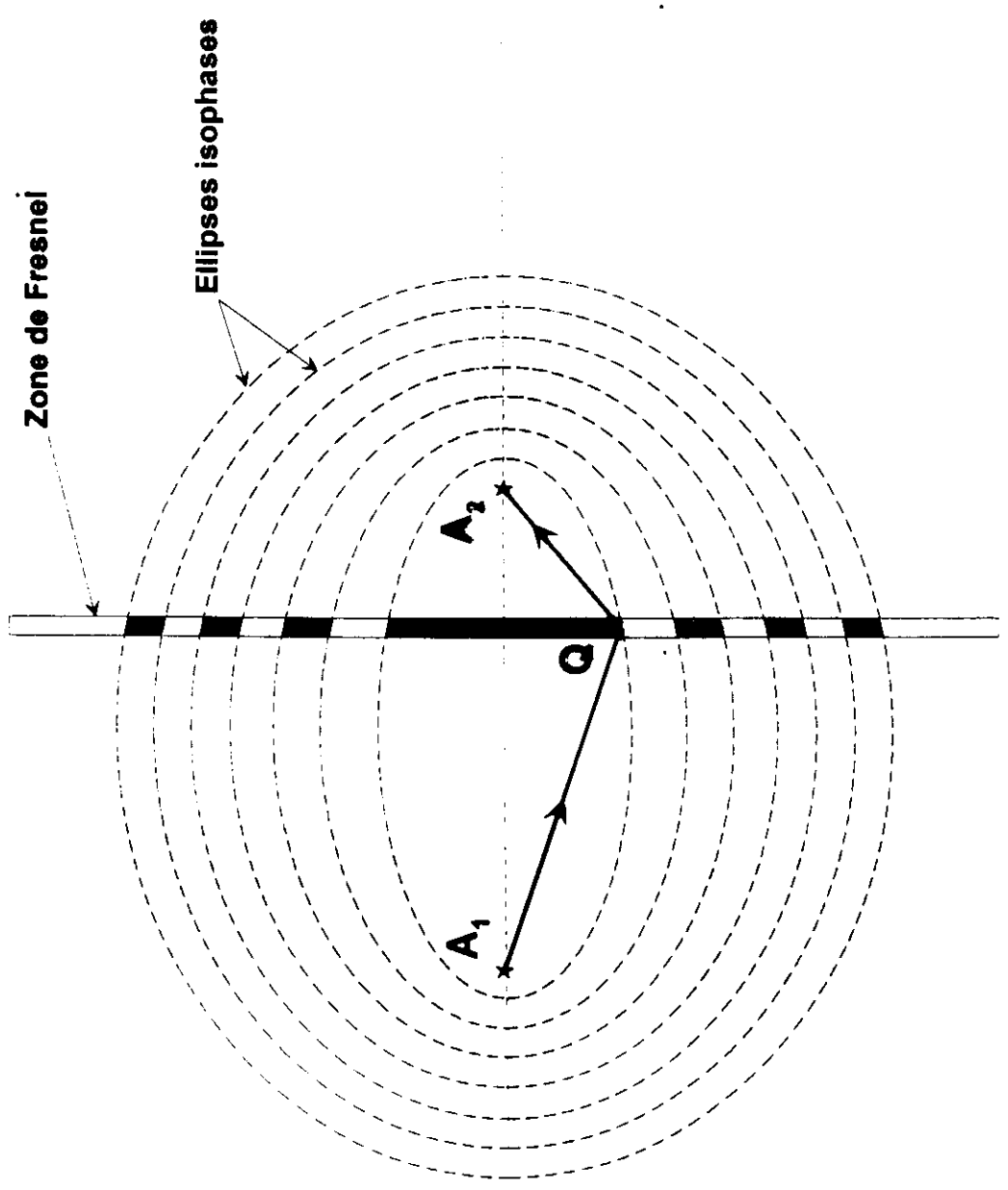
BRAGG
DIFFRACTION

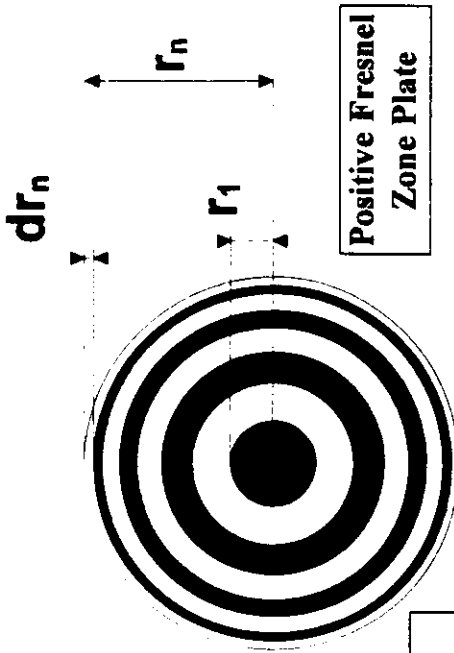
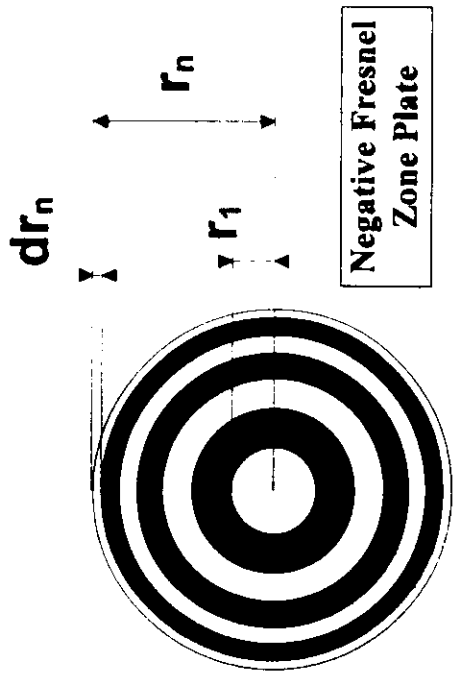
GRATINGS
ZONE PLATE



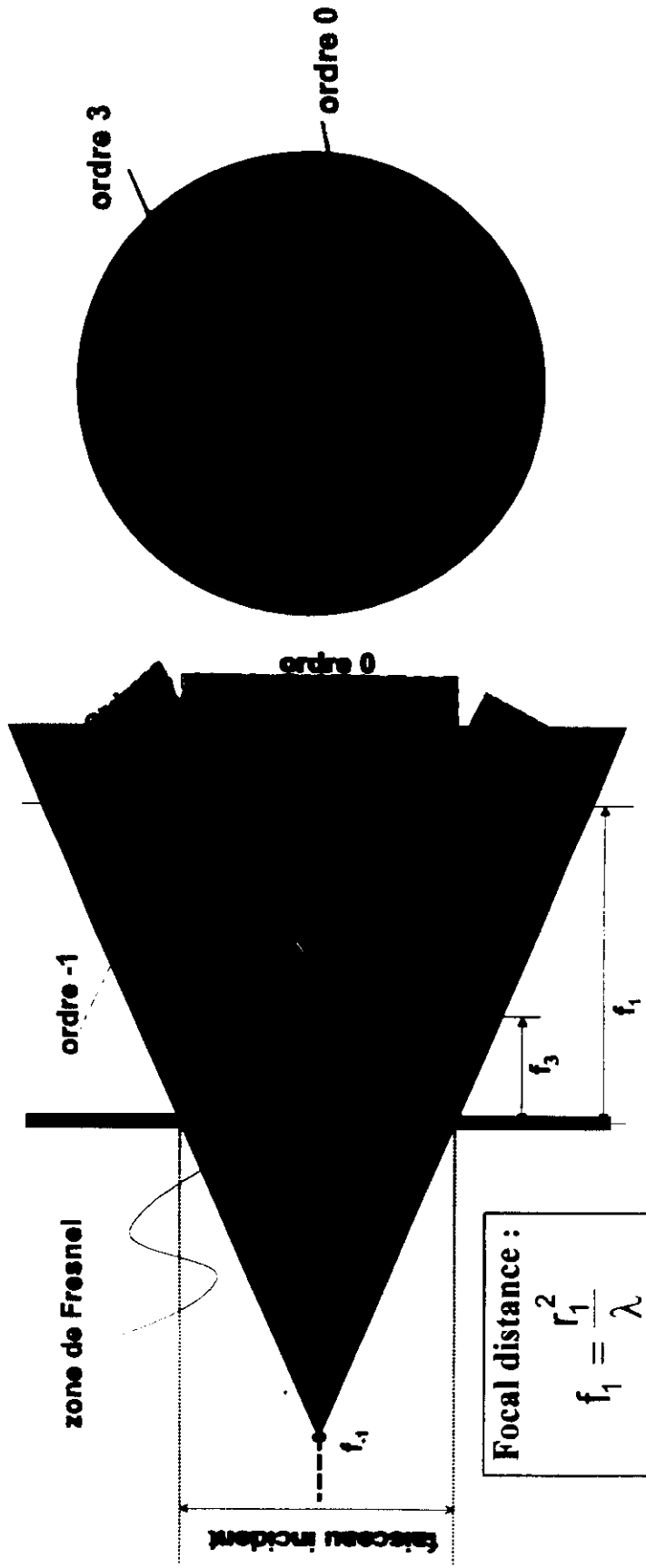
FRESNEL
DIFFRACTION





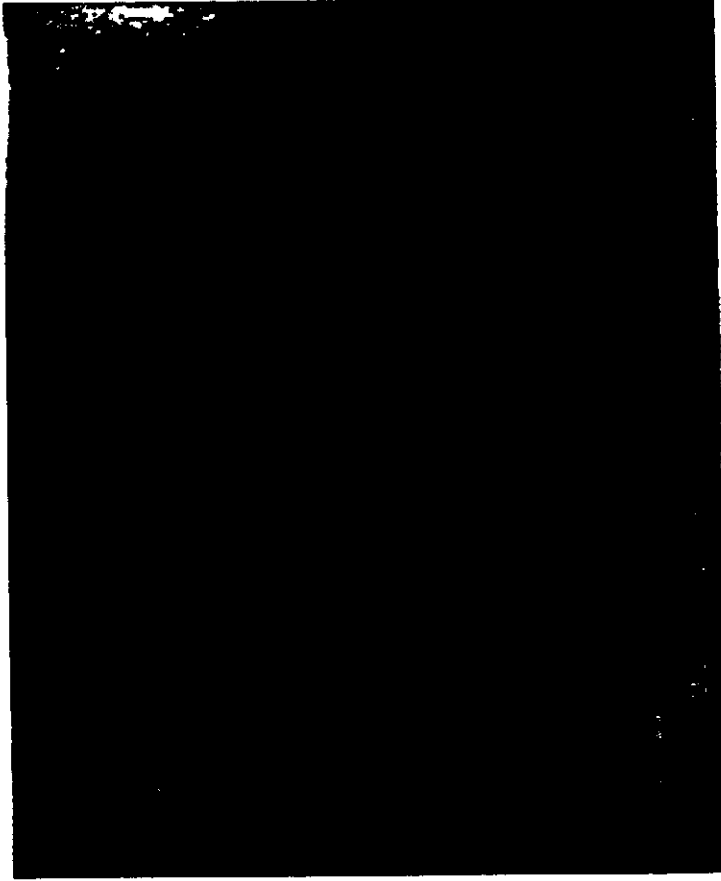


$$r_n = r_1 \cdot \sqrt{n}$$



Focal distance :

$$f_1 = \frac{r_1^2}{\lambda}$$



$N=68$ zones
 $r_1=6,63 \mu\text{m}$
 $D=110 \mu\text{m}$
 $r_n=0,4 \mu\text{m}$
 $e=0,5 \mu\text{m}$



A) MULTILAYER FABRICATION

Sputtering of the two materials.

B) MICROLITHOGRAPHY TECHNICS

TWO STEPS :

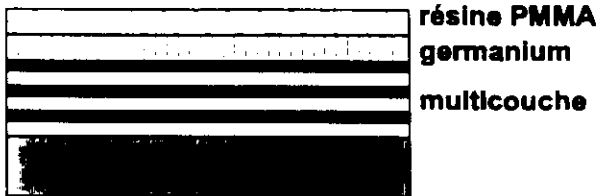
- 1) Electronic lithography**
Writing of " THE HOLOGRAM" at the multilayer surface.
- 2) Reactive ion etching**
Transfer of " THE HOLOGRAM" in the multilayer.



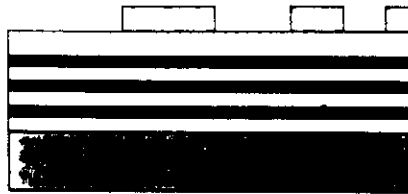
1) Substrat de Silicium
poli



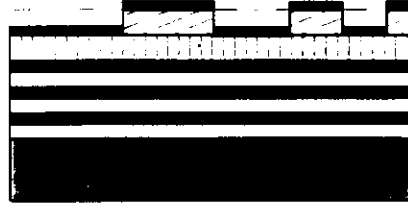
2) Dépôt d'une multicouche



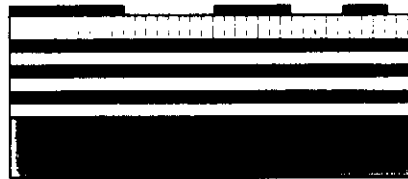
3) Dépôt d'une couche de
Germanium et de la résine PMMA



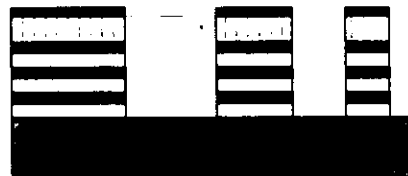
4) Ecriture par faisceau d'électrons
et développement de la résine PMMA



5) Dépôt de Nickel



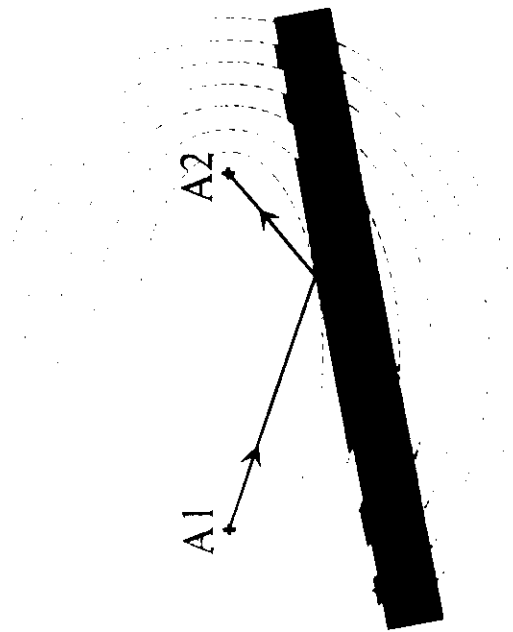
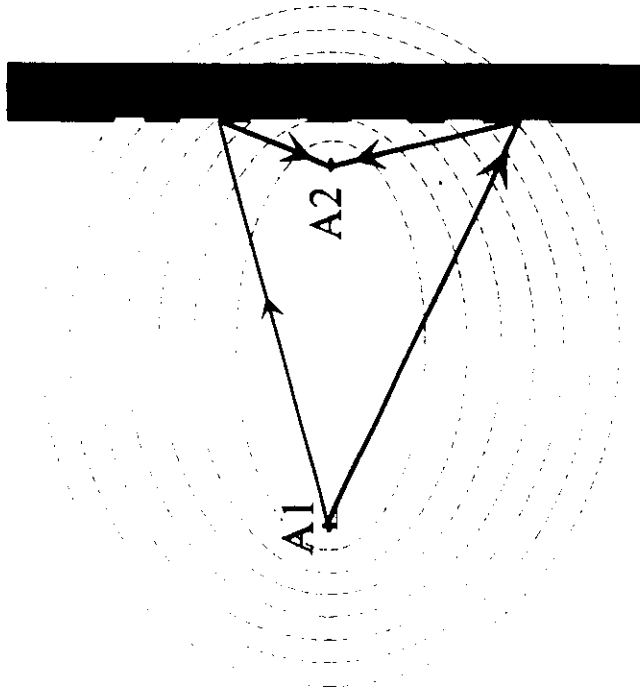
6) "Lift-off" du Nickel par élimination
de la résine et du métal supporté



7) Gravure ionique réactive
dans un plasma fluoré



8) Elimination du masque de Nickel
et du Germanium



NEW KIND OF FOCUSING AND IMAGING OPTICS

FOR THE X-RAY AND UV ENERGY RANGES

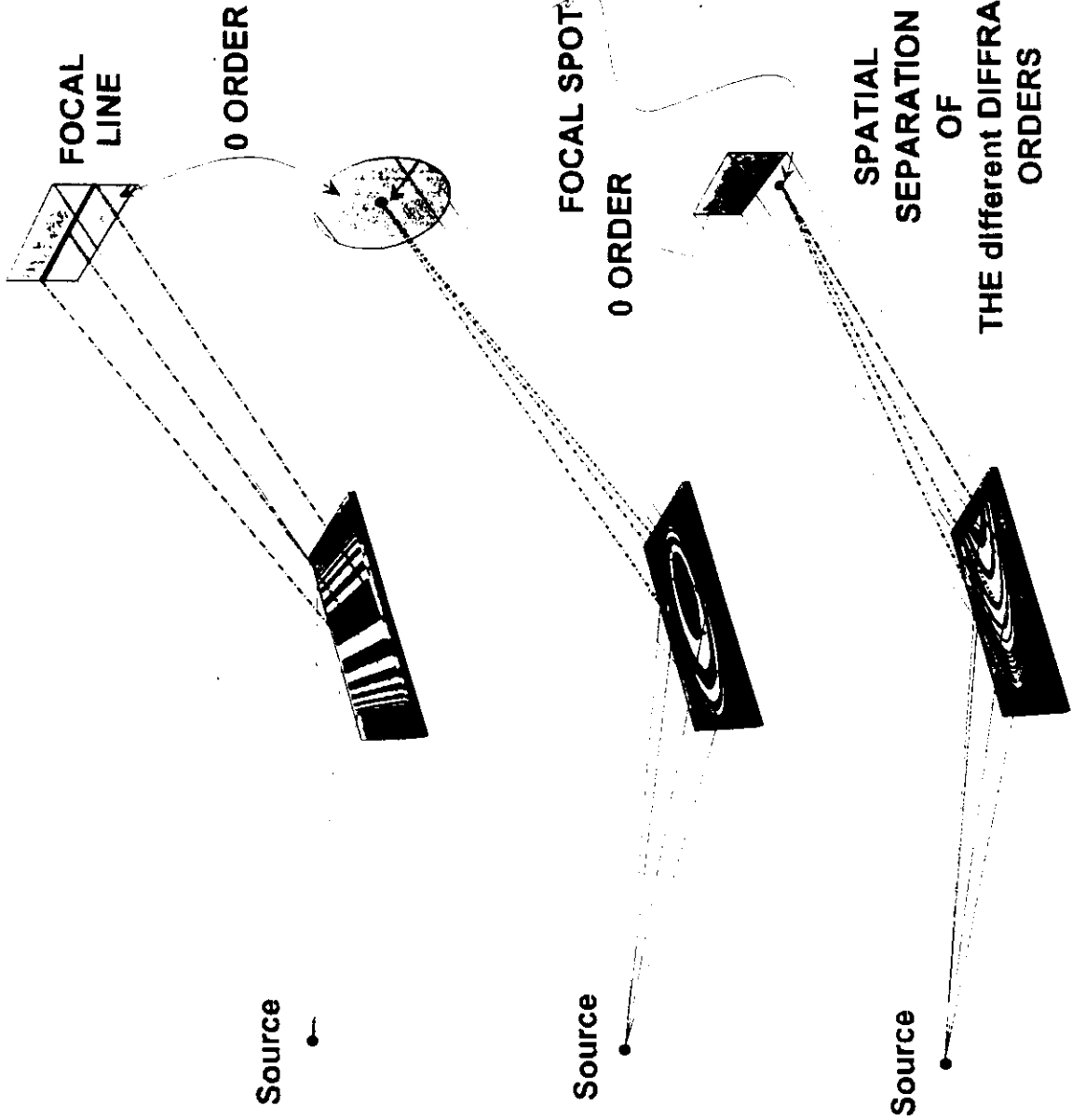
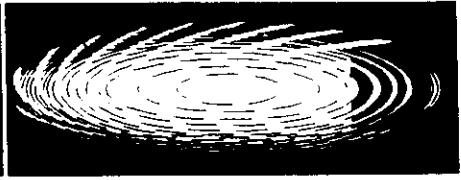
LINEAR LENS



ELLIPTICAL LENS

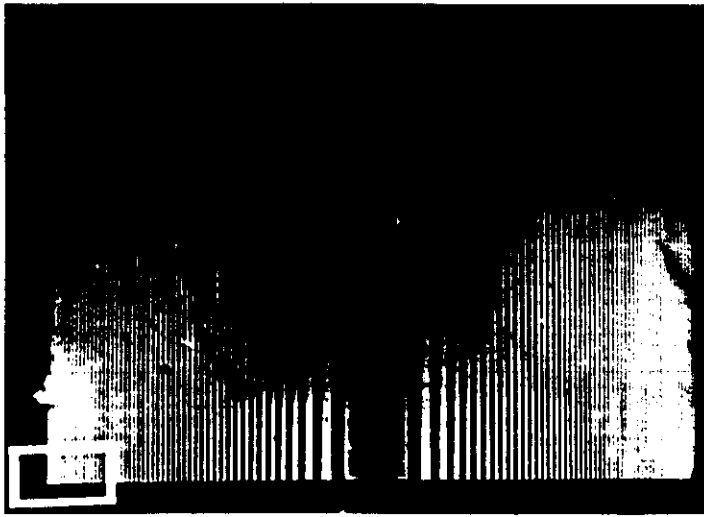


ELLIPTICAL OFF-AXIS LENS





210 μm

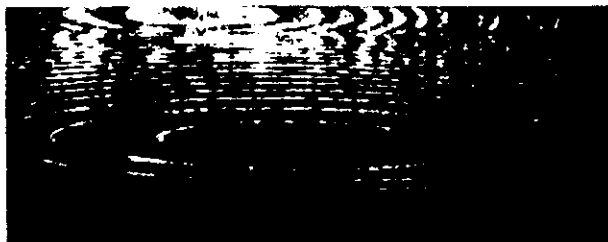


Zoom

**Lentille de Bragg-Fresnel
linéaire positive**



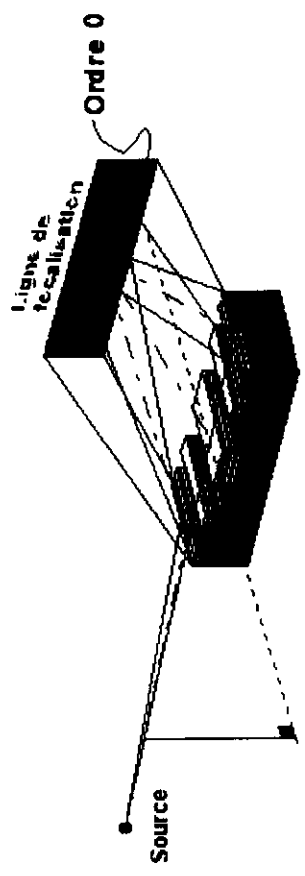
2 μm



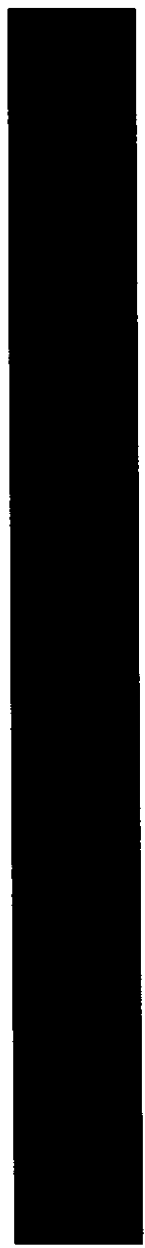
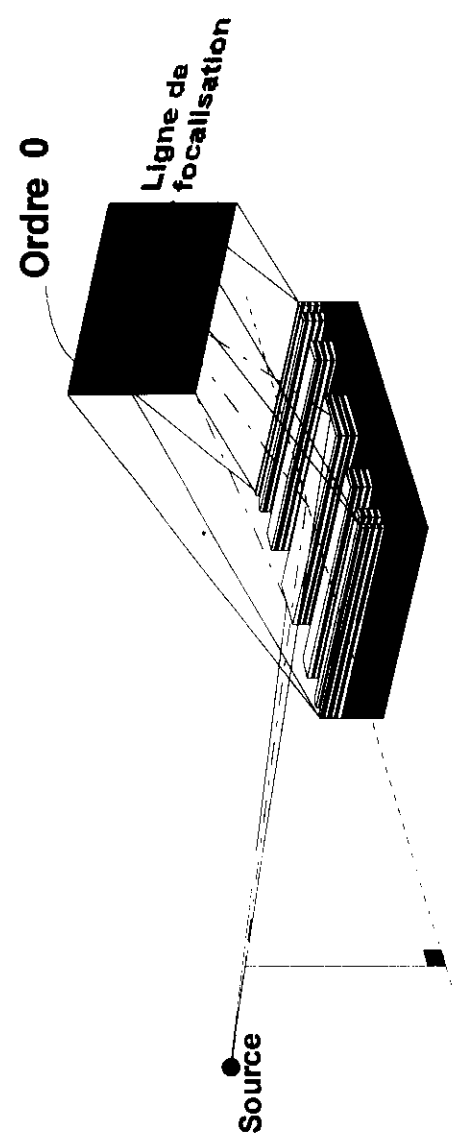
**Zones centrales
Lentille de Bragg-Fresnel elliptique positive**



**CONICAL
DIFFRACTION**

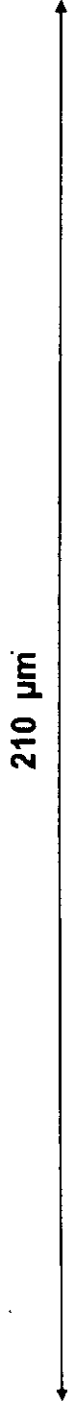


**CLASSICAL
DIFFRACTION**

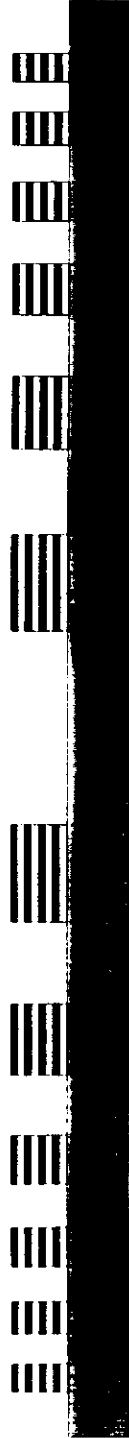




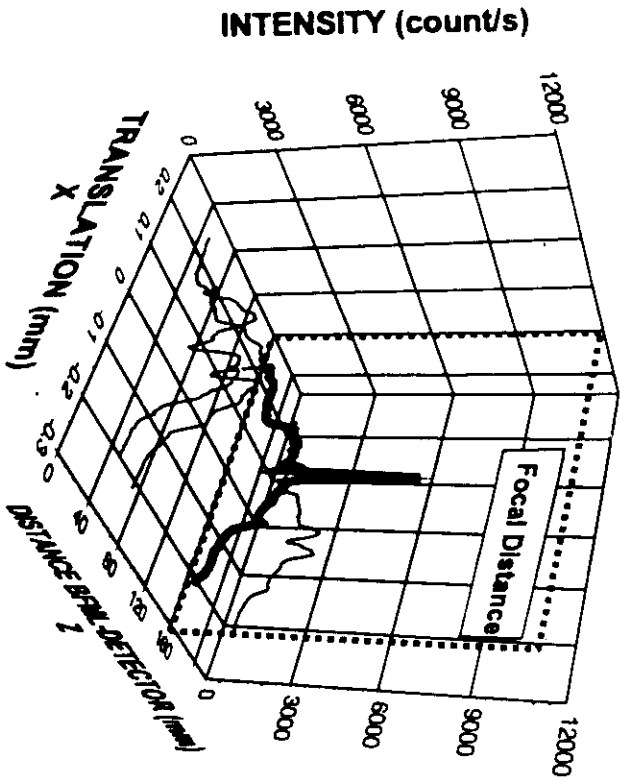
Multilayer W/SI 25 paires d= 53 Å E=1750 eV



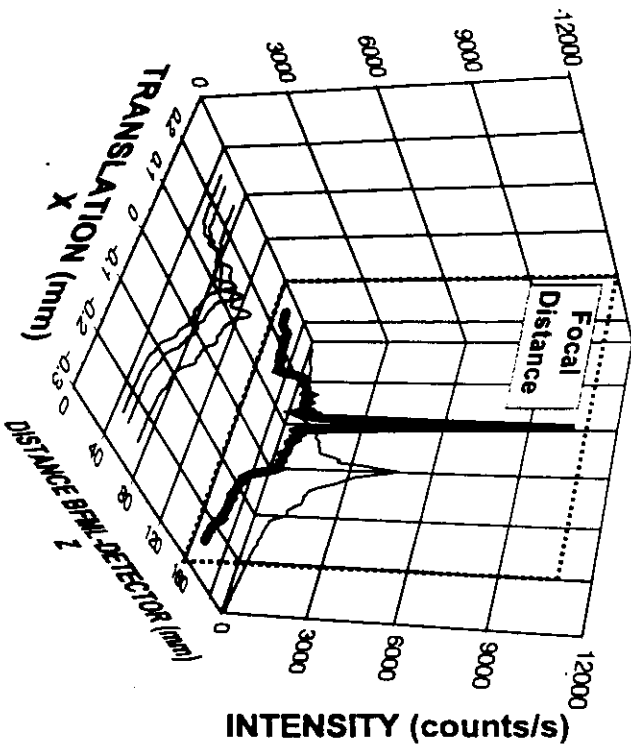
100 TRAITS POSITIVE



NEGATIVE



NEGATIVE LENS

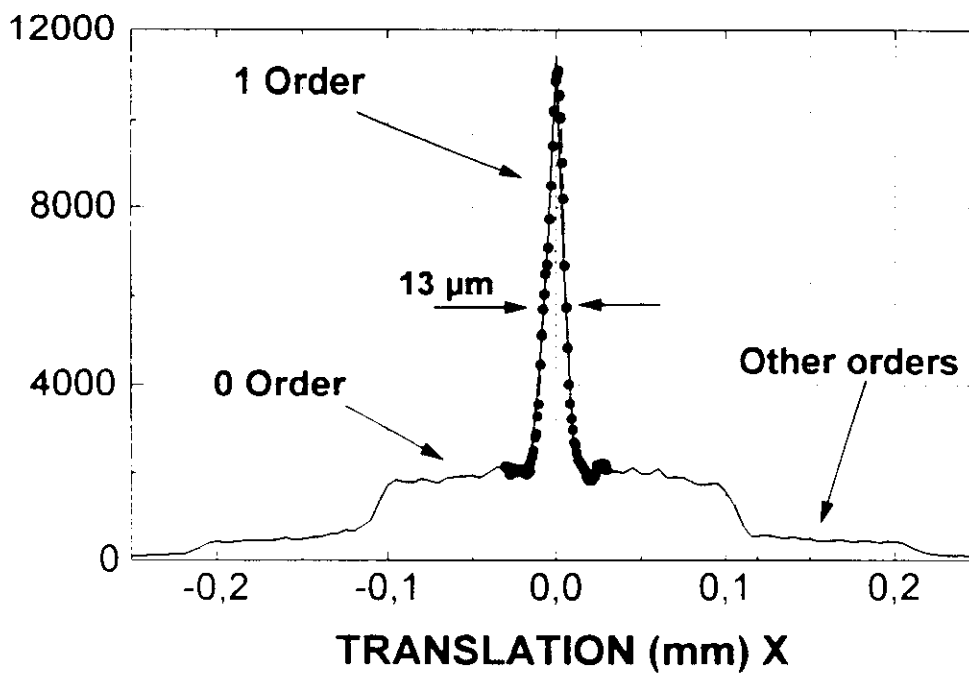
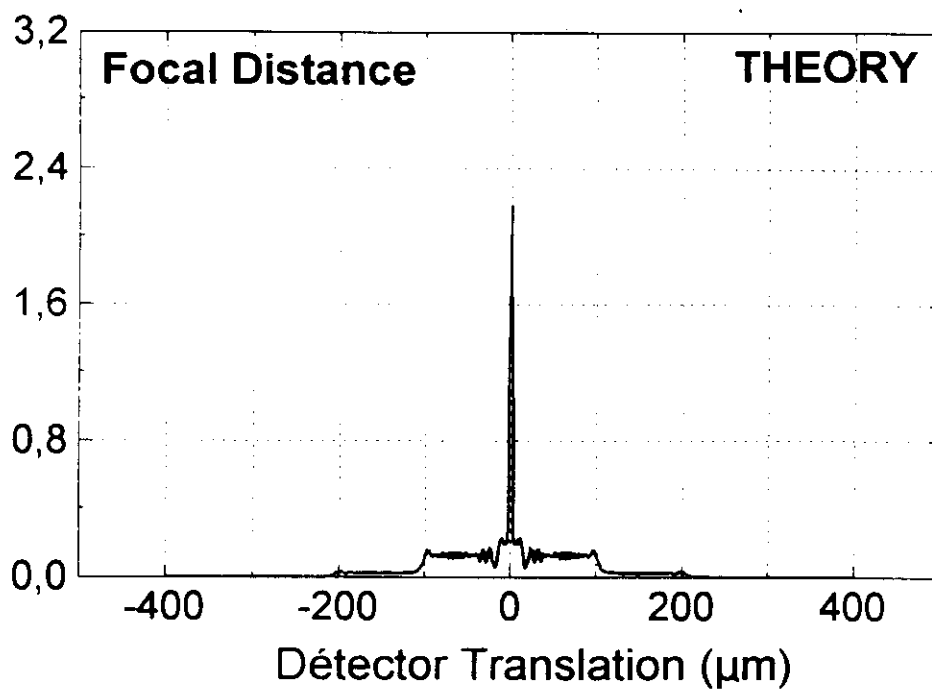


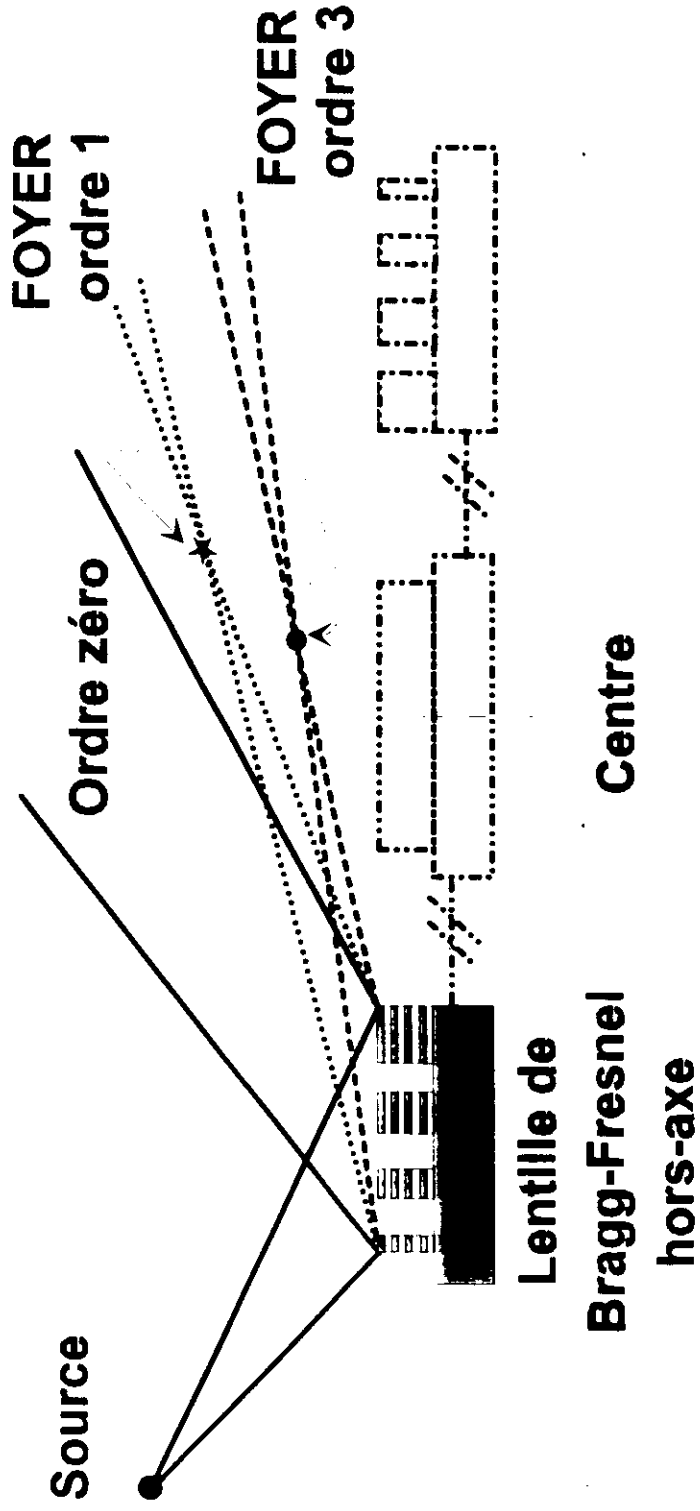
POSITIVE LENS

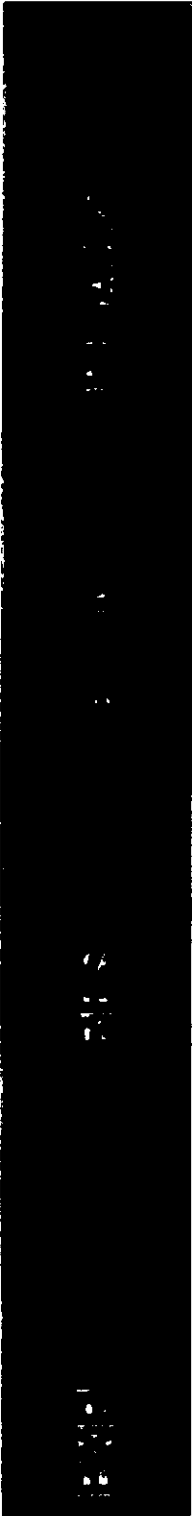
BRAGG-FRESNEL LENSES used in the



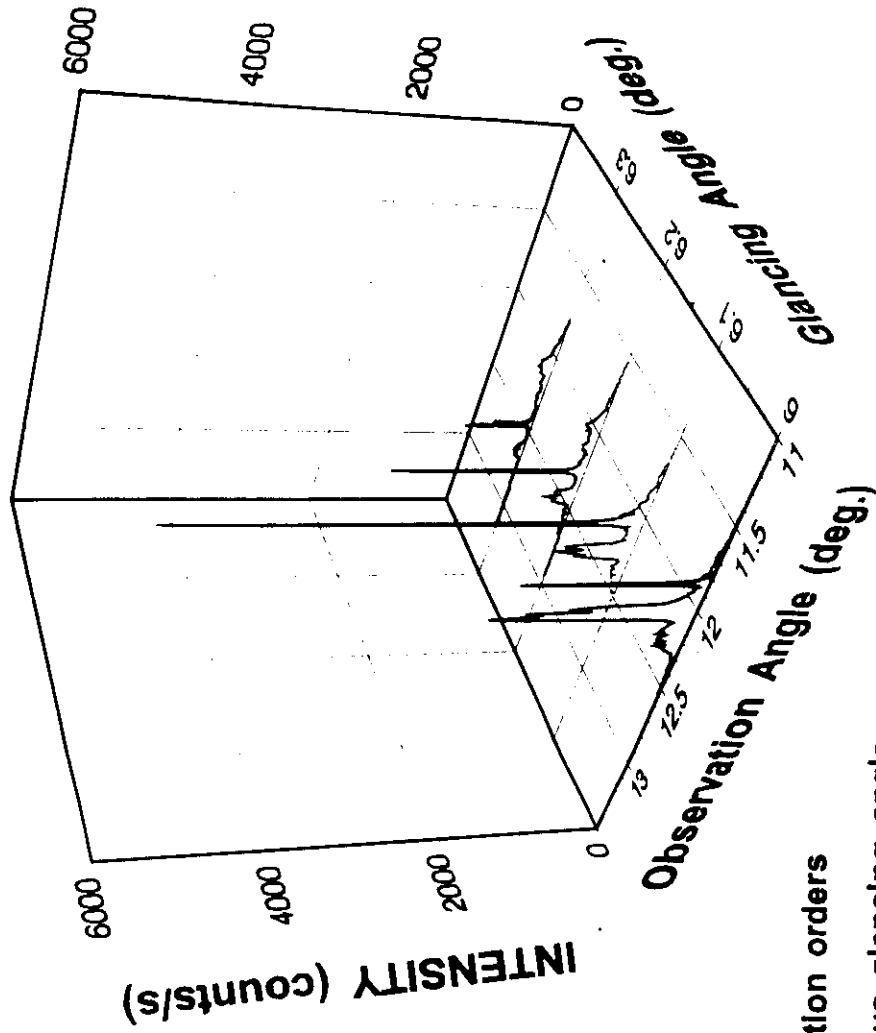
mode







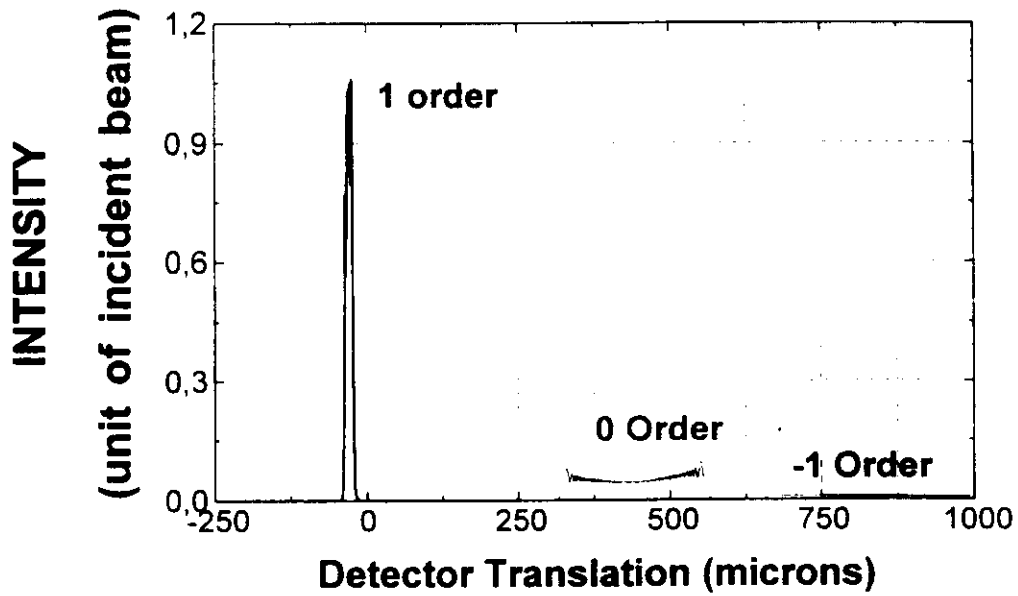
W/Sl
d=34 Å 65 bilayers
E=1750 eV
minimum zone width 0.9 μm
maximum zone width 1.5 μm



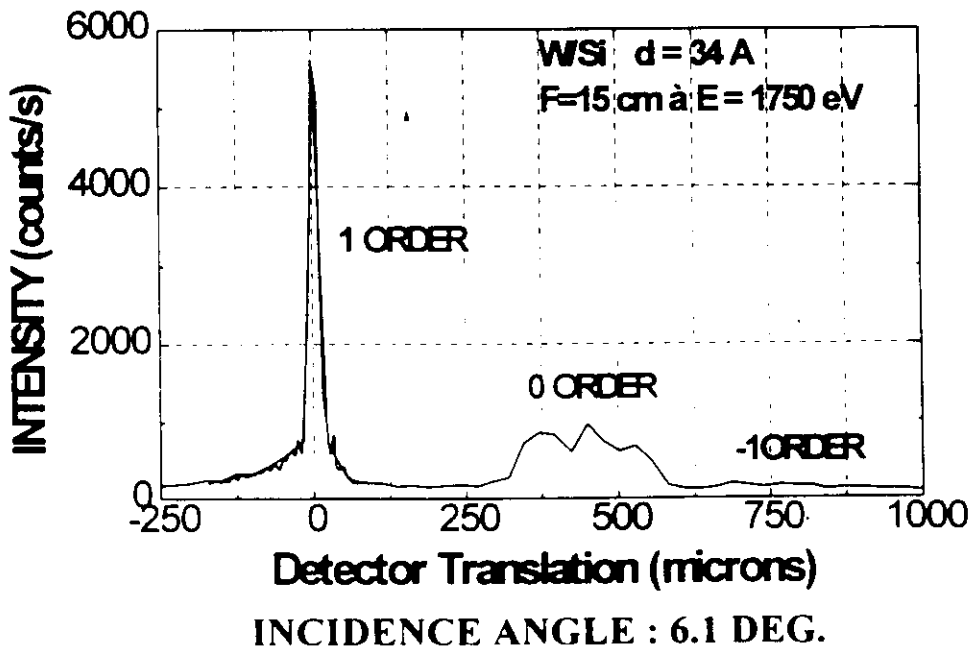
Separation of the different diffraction orders
Optimisation of the Intensity versus glancing angle



THEORY

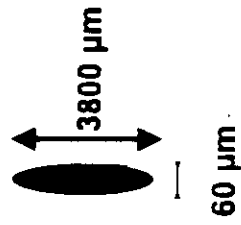


EXPERIENCE

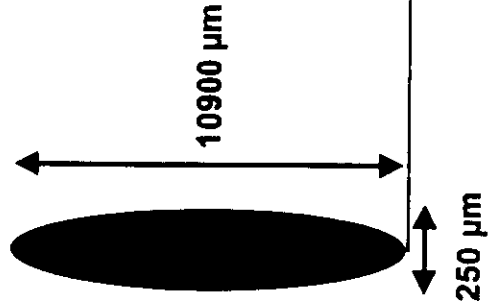




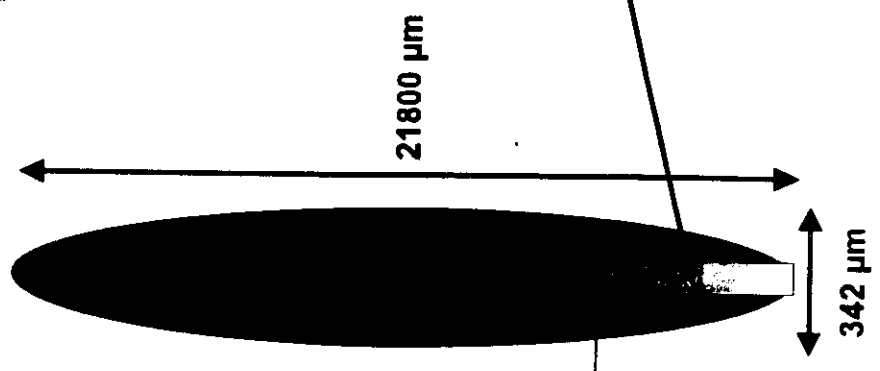
30 traits
 $\delta x = 0.26 \mu\text{m}$
 $\delta y = 15.6 \mu\text{m}$



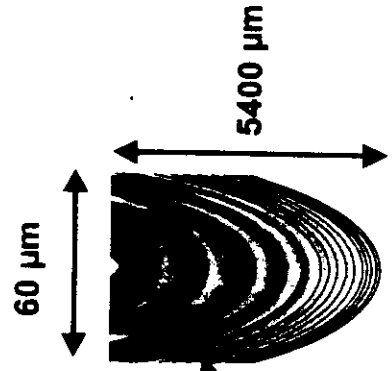
250 traits
 $\delta x = 0.1 \mu\text{m}$
 $\delta y = 5.9 \mu\text{m}$



1000 traits
 $\delta x = 0.04 \mu\text{m}$
 $\delta y = 2.7 \mu\text{m}$



Paramètres des lentilles
 $\lambda = 1 \text{ \AA}$ $F = 15 \text{ cm}$
 $\theta = 0.8 \text{ deg.}$

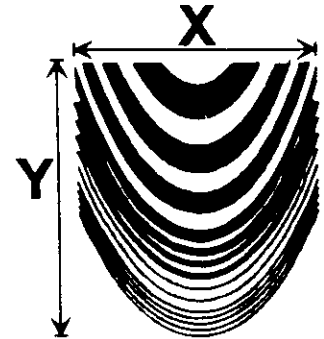


Material	Period : d_{∞} (Å)	γ	E / λ (eV / Å)	Number of bilayers
W / C	32	0.31	2535 / 4,89	65

Multilayer parameters

Number of grooves	size (μm) x direction / y direction	size of the first zone y direction (μm)	size of the last zone y direction (μm)	size of the zone in the center y direction (μm)
500 (du 12810 ^{ième} au 18810 ^{ième})	200,1 / 2850,1	0,42	0,33	0,37

Parameters of the off-axis elliptical lens



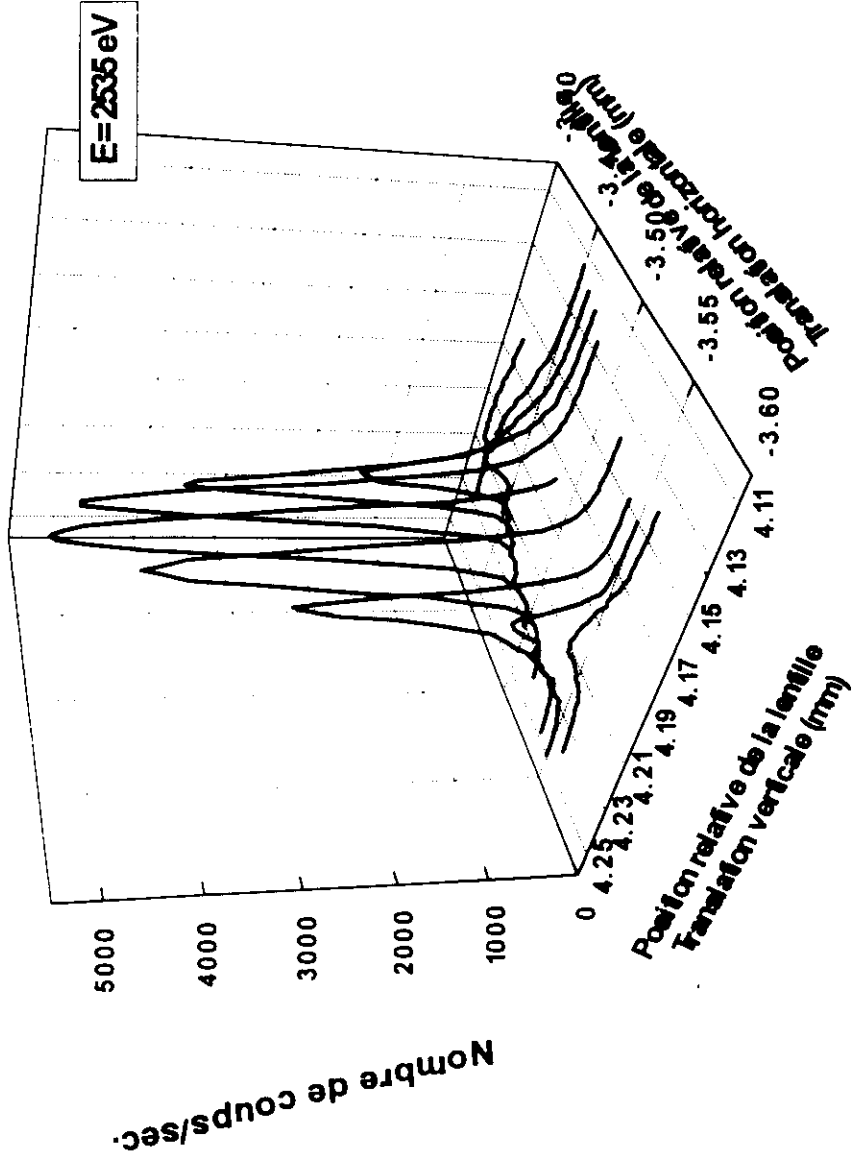
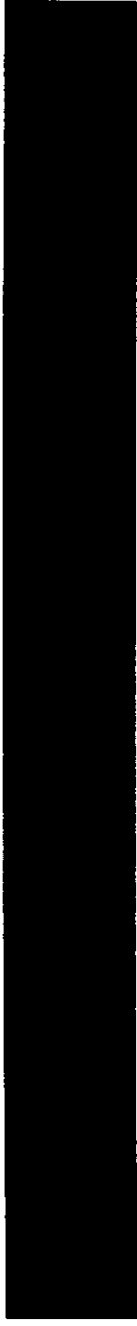
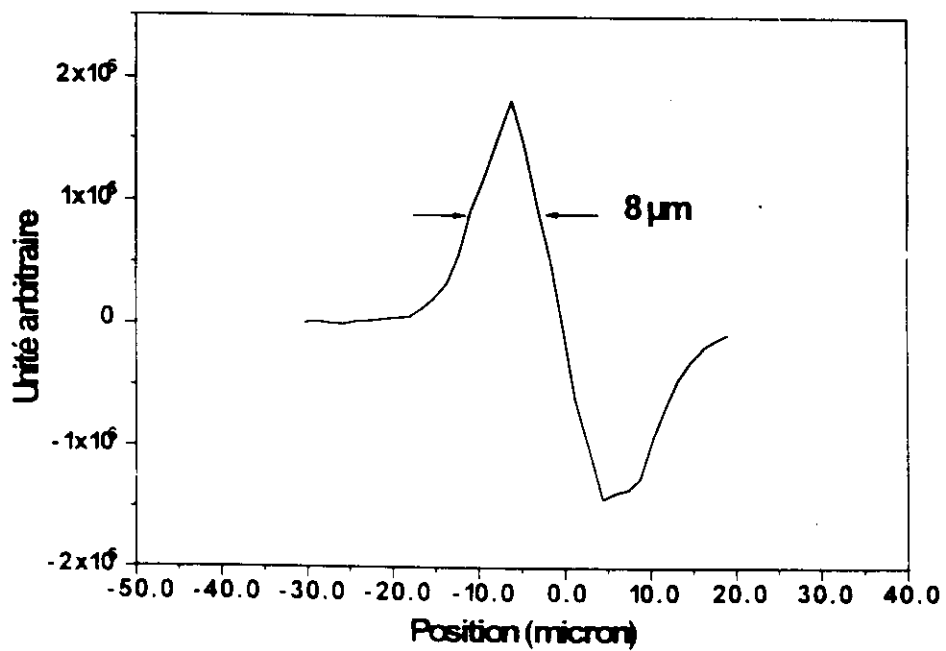
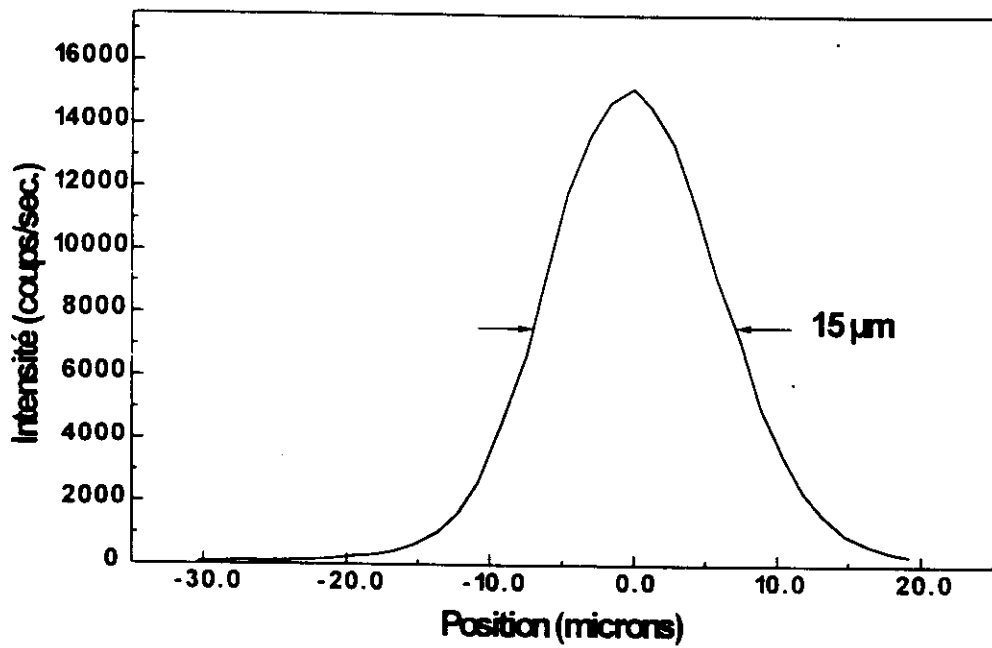
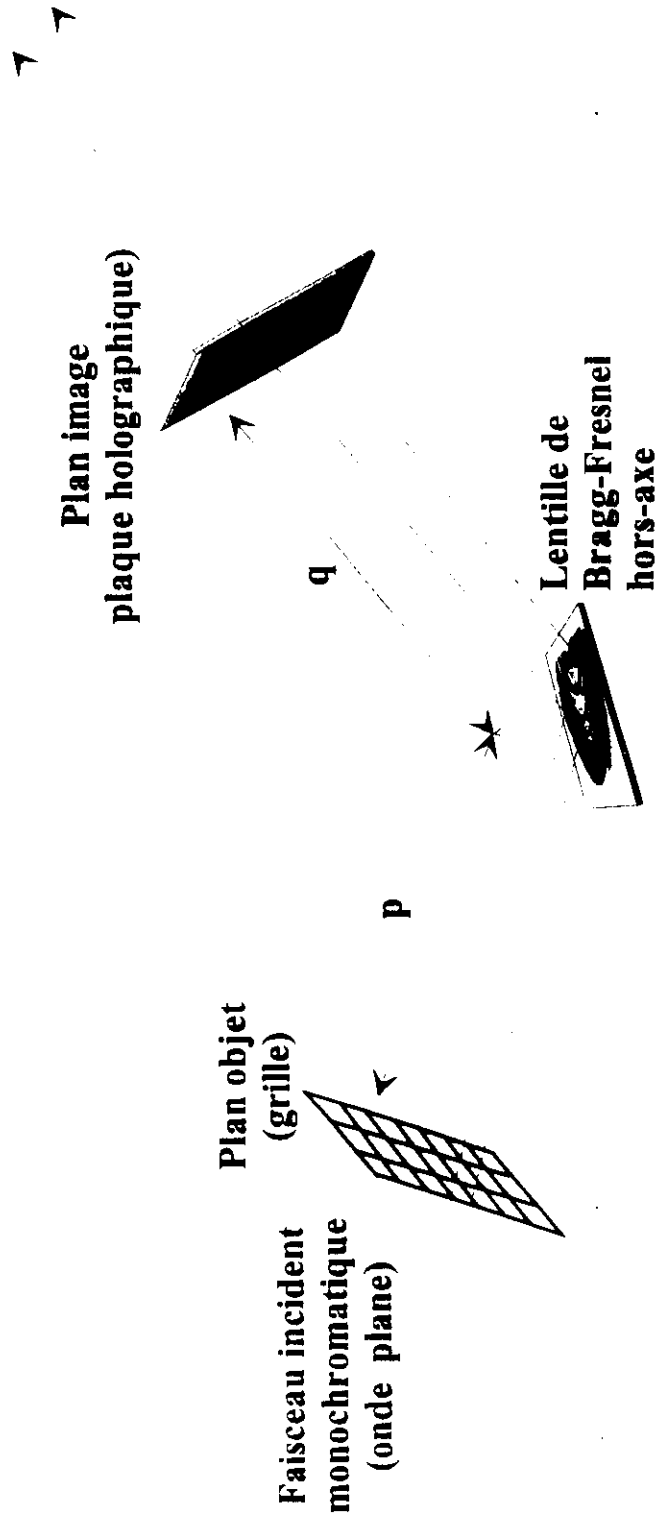


Image of the source of Super ACO ring (LURE) with the off-axis Bragg-Fresnel zone
(proportional counter $d = 15 \mu\text{m}$)

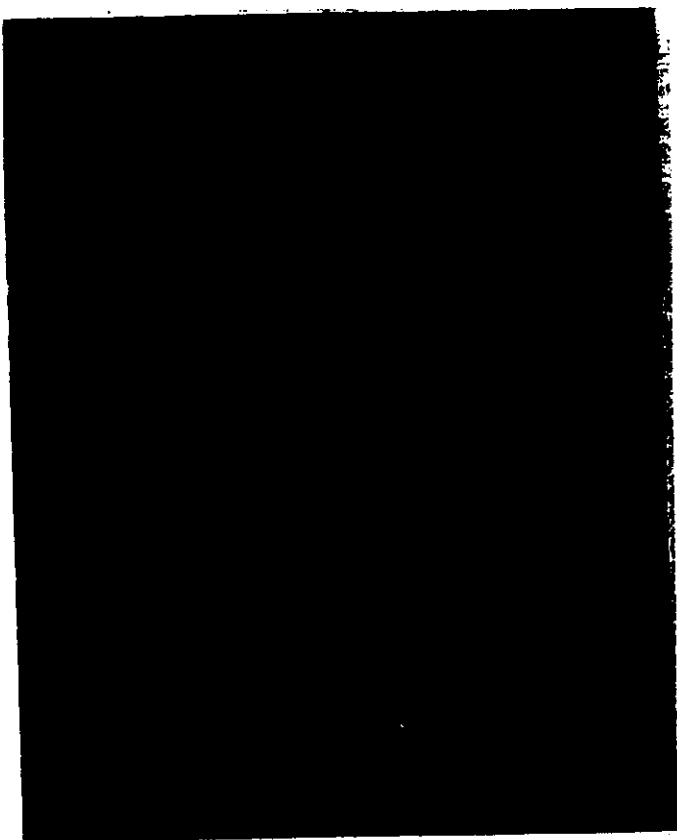


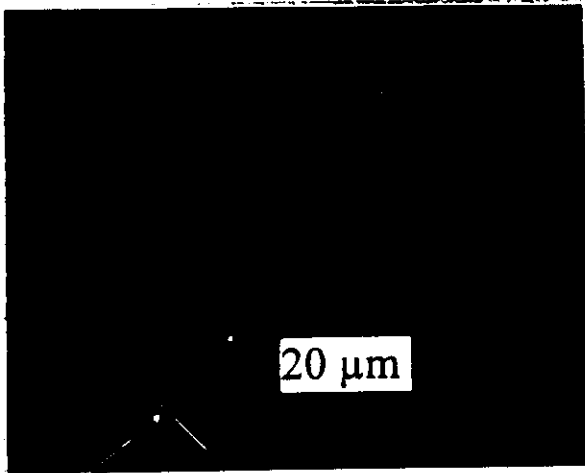


With : $p=32$ cm et $q=30$ cm

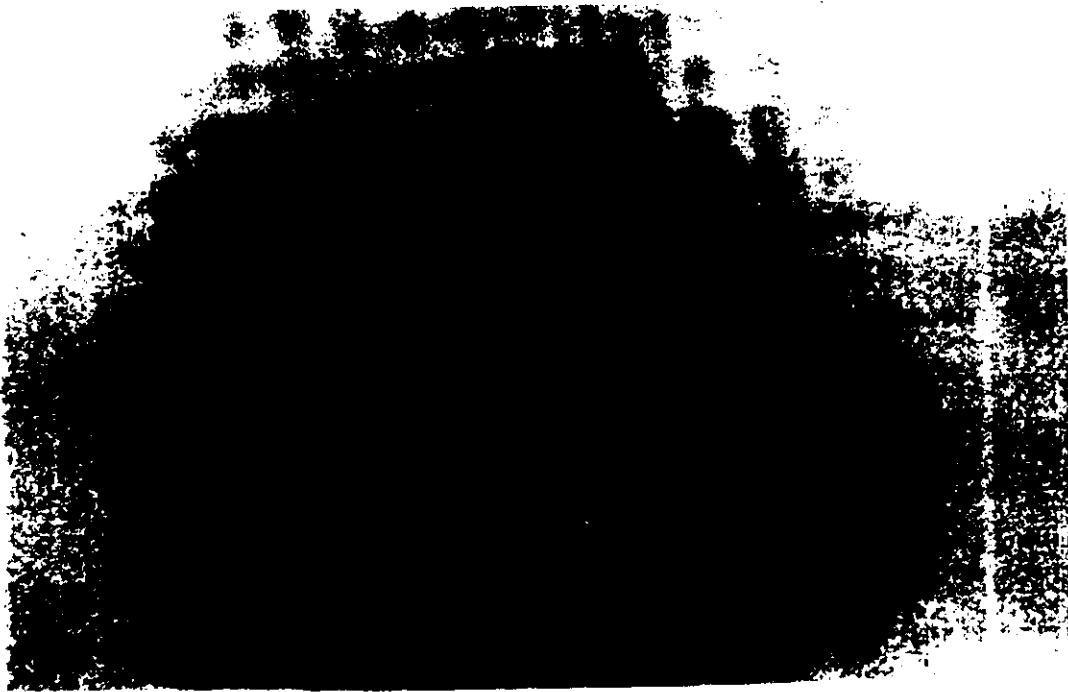
$$G=30/32=0,94$$

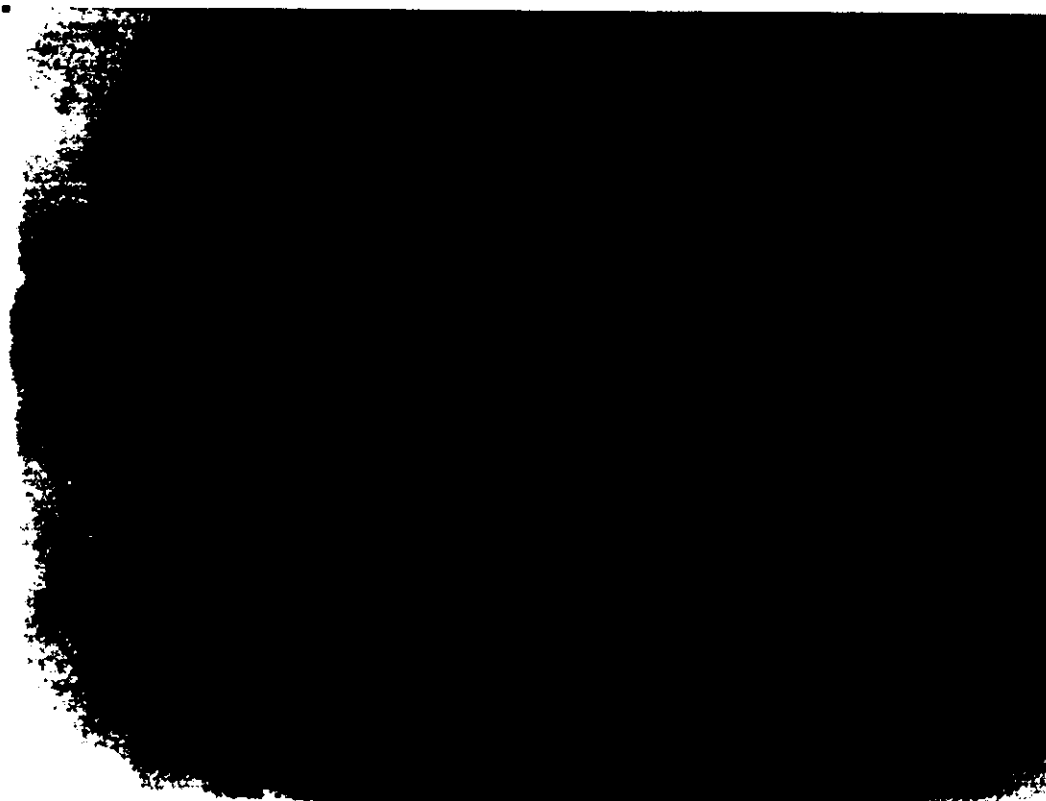
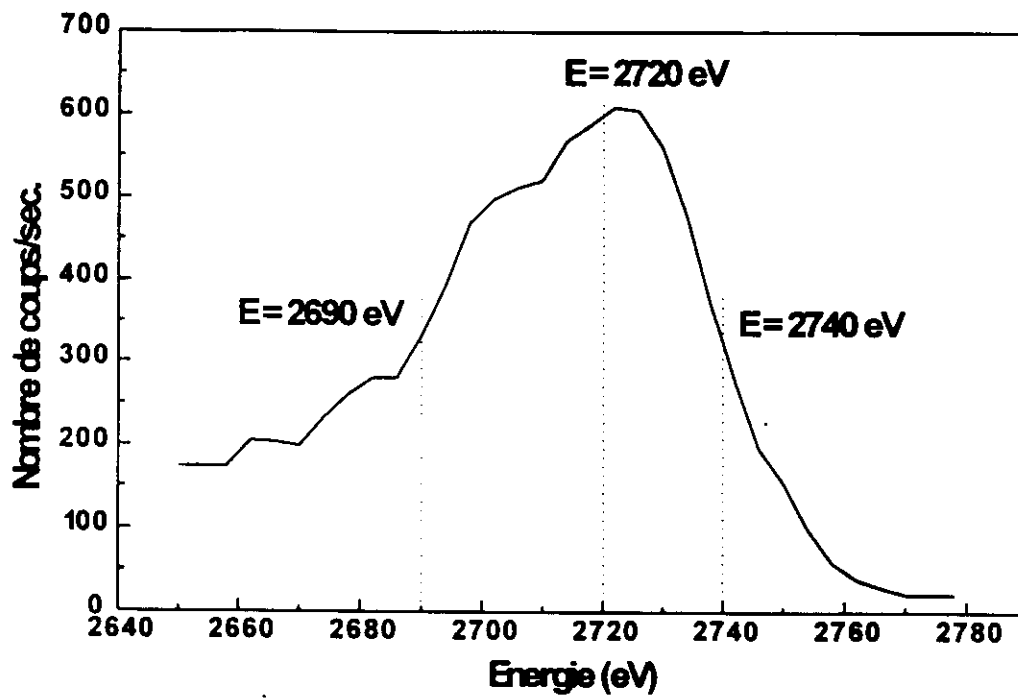
Test object: grids with bars
of 15 μm length and periods
of 50, 75, 100, 150 μm

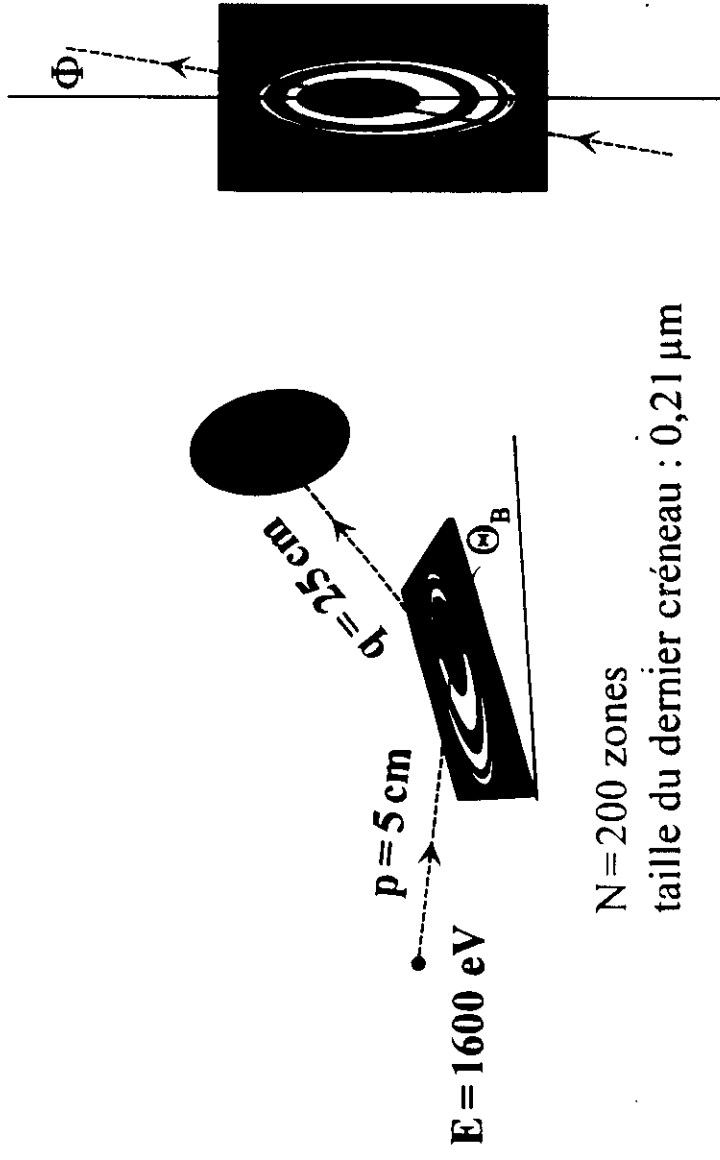




Test object : 3 grids
superimposed with bars of
5,5 μm length and step of 20 μm





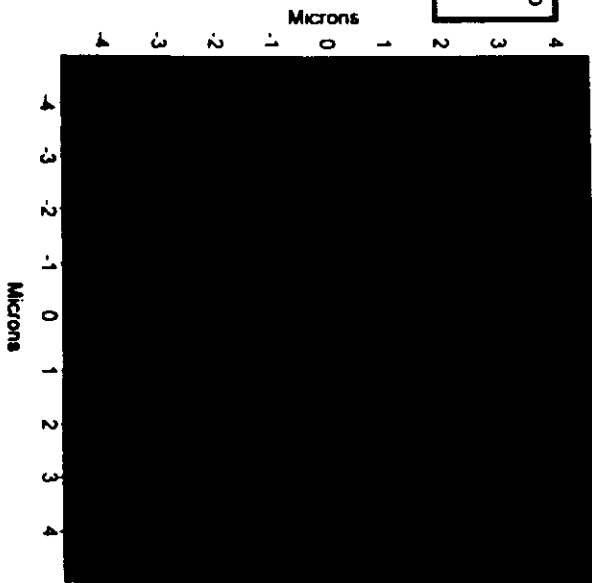


$N = 200$ zones
taille du dernier créneau : $0,21 \mu\text{m}$

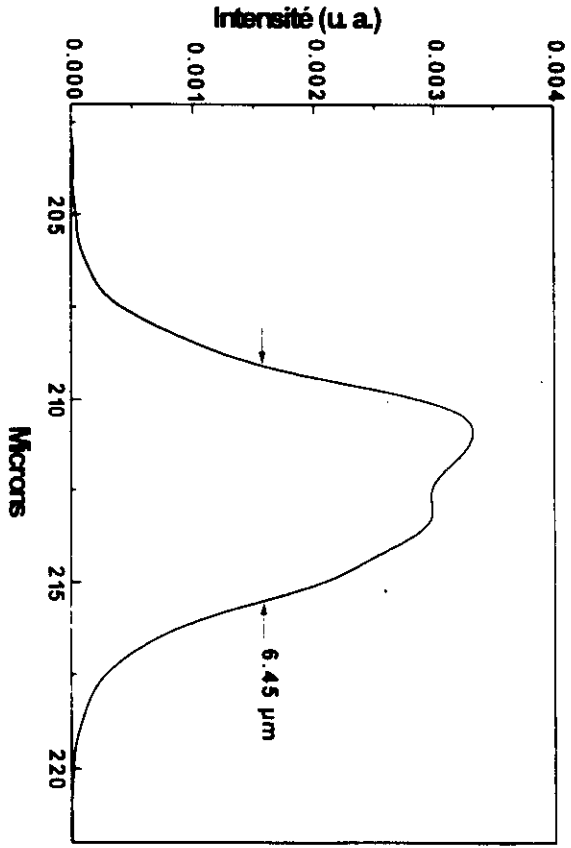
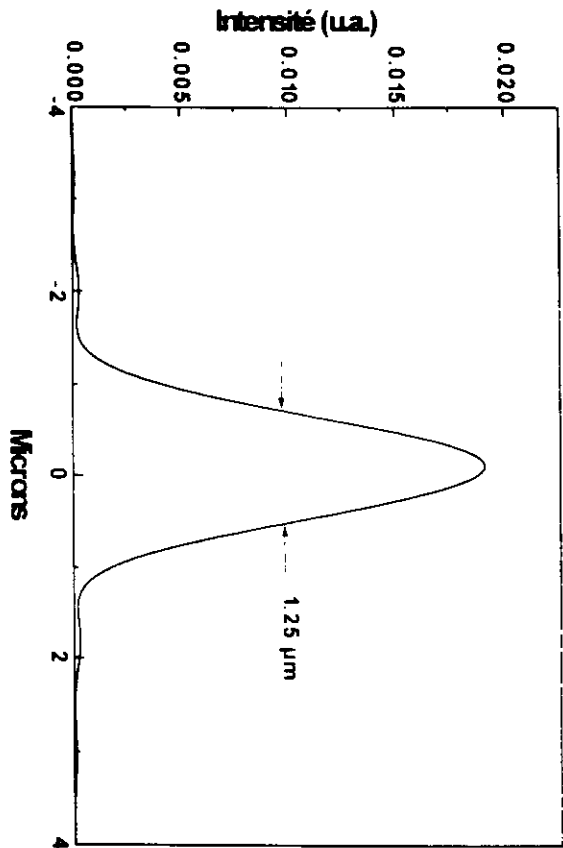
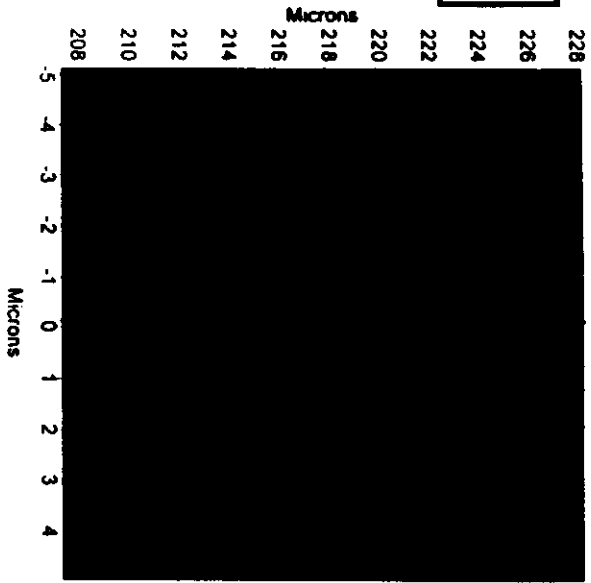
Multilayer : W/Si, 65 bilayers of $2,55 \text{ nm}$, $\gamma = 0,5$



$\Theta = \Theta_B = 8,86^\circ$
 $\Phi = 0^\circ$

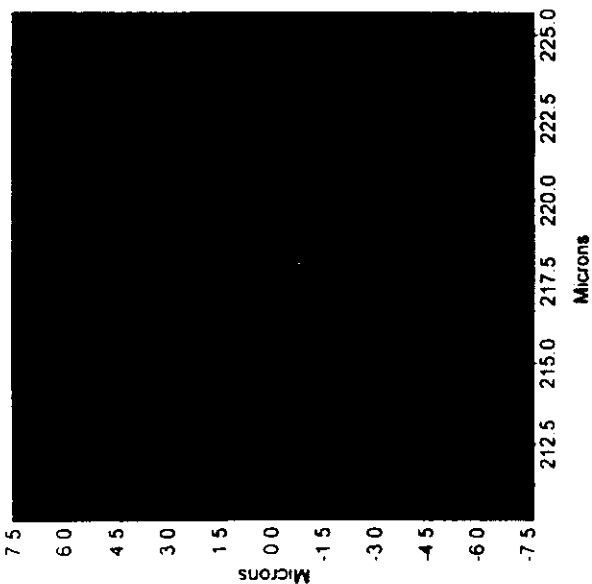


$\Theta = \Theta_B + 0,05^\circ$
 $\Phi = 0^\circ$

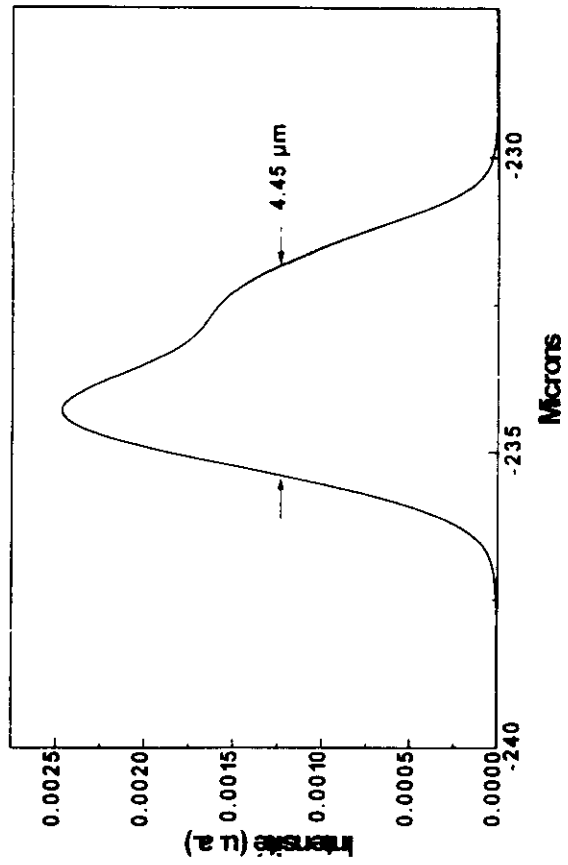
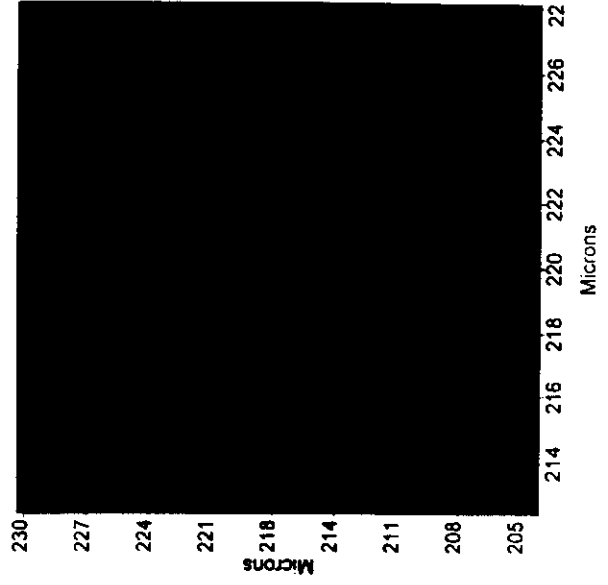


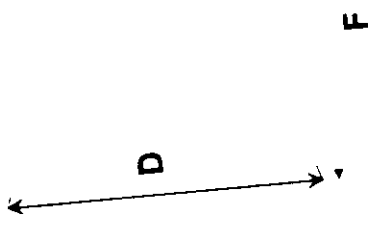
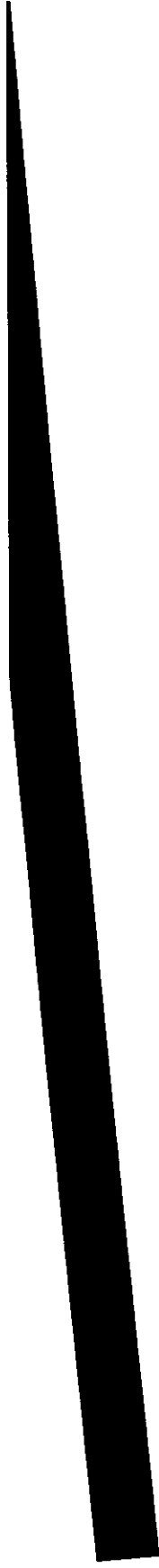


$$\Theta = \Theta_B$$
$$\Phi = +0,05^\circ$$

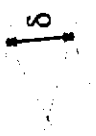


$$\Theta = \Theta_B + 0,05^\circ$$
$$\Phi = +0,05^\circ$$

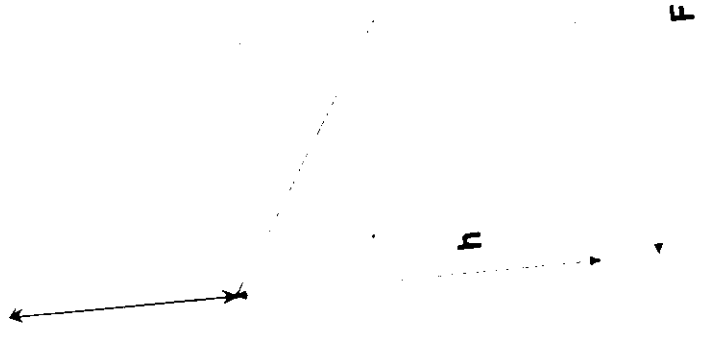




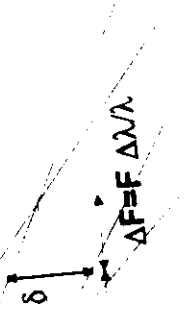
$$\delta = D \frac{\Delta\lambda}{\lambda}$$

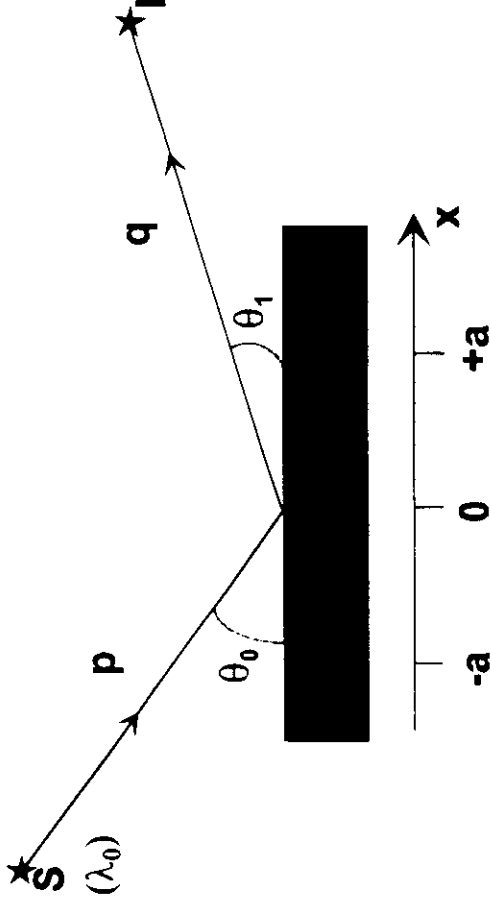


$$\Delta F = F \frac{\Delta\lambda}{\lambda}$$



$$\delta \cong 2h \frac{\Delta\lambda}{\lambda}$$





The grating function $C(x)$ of a lens is defined by : $C(x) = s(p, x, \theta_0) + s(q, -x, \theta_1)$

$$\text{where } s(a, x, \theta) = \sqrt{a^2 + x^2} + 2ax \cos(\theta)$$

The profil of a Bragg-Fresnel multilayer lens is choosenby placing the zone borders at positions

$$r_n \text{ such that : } C(r_n) - C(r_{n-1}) = \frac{\lambda_0}{2}$$

For the wavelenght $\lambda_0 + \Delta\lambda$, the optical path function is :

$$C(x) = s(p, x, \theta_0) + s(q', -x, \theta') - \frac{\lambda_0 + \Delta\lambda}{\lambda_0} C(x) = s(q', -x, \theta') - s(q, x, \theta_1) - \frac{\Delta\lambda}{\lambda_0} C(x)$$

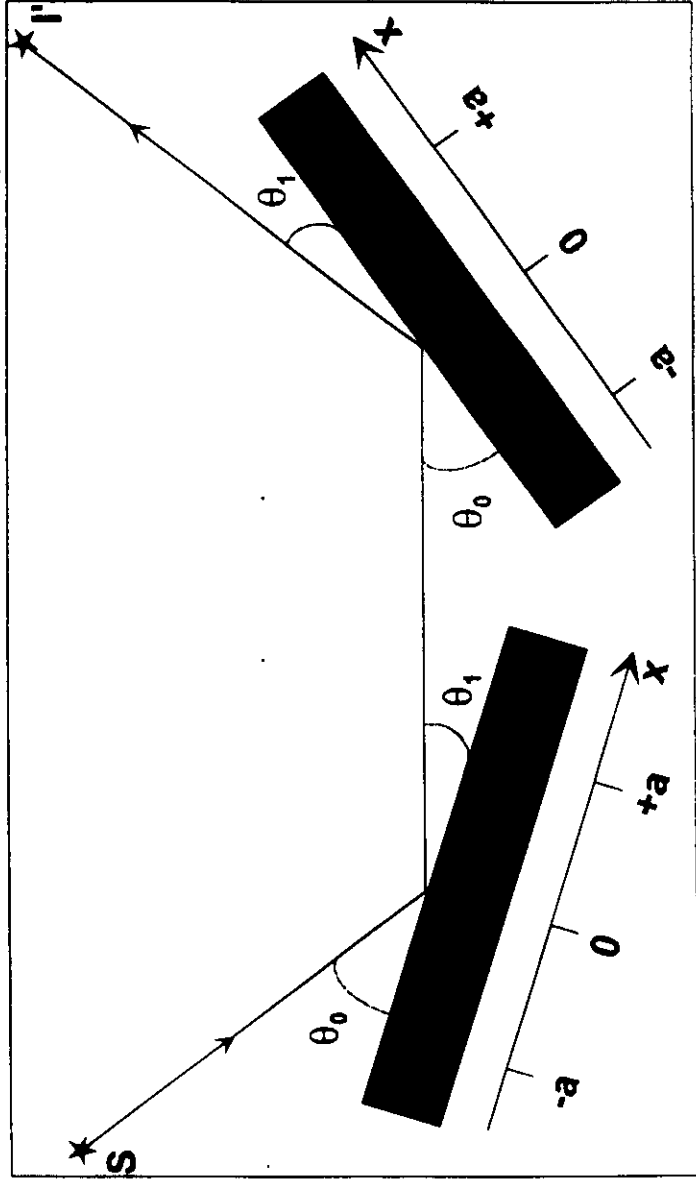
With a Taylor development like : $s(a, x, \theta) \cong a + x \cos(\theta) + \frac{x^2}{a}$

$$(x)_{q=0}^{(0)=q} = \frac{\Delta\lambda}{\lambda_0} \left[q + p + x(\cos(\theta_1) - \cos(\theta_0)) + \frac{x^2}{2} \left[\frac{\sin^2(\theta_0)}{p} + \frac{\sin^2(\theta_1)}{q} \right] \right]$$

The linear term in x is absent in centered lenses and, for off-axis lenses, can cause strong chromatic aberrations.

A double reflection with two equivalent off-axis lenses can reduce the chromatic aberrations (linear term of $P(x)$).

If the distance between lenses is small compared to the focal one, one can say that, from a geometrical point of view, a ray hitting the first lens at x , hits the second at $-x$. This way, the linear term cancel each other out and aberrations are reduced to the ones occurring in centred lenses.



Laser
à 1.06 μm

Laser
à 0.53 μm

45°

Cible
aluminium

Cristal
doubleur

Grille

0,5 cm

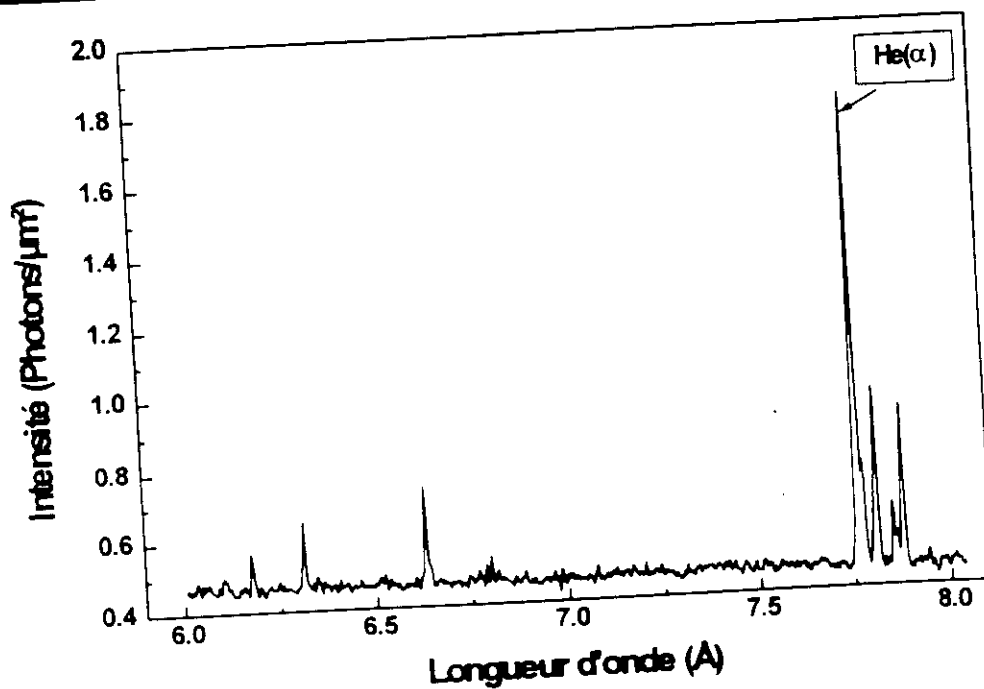
5 cm

Lentille de
Bragg-Fresnel

25 cm

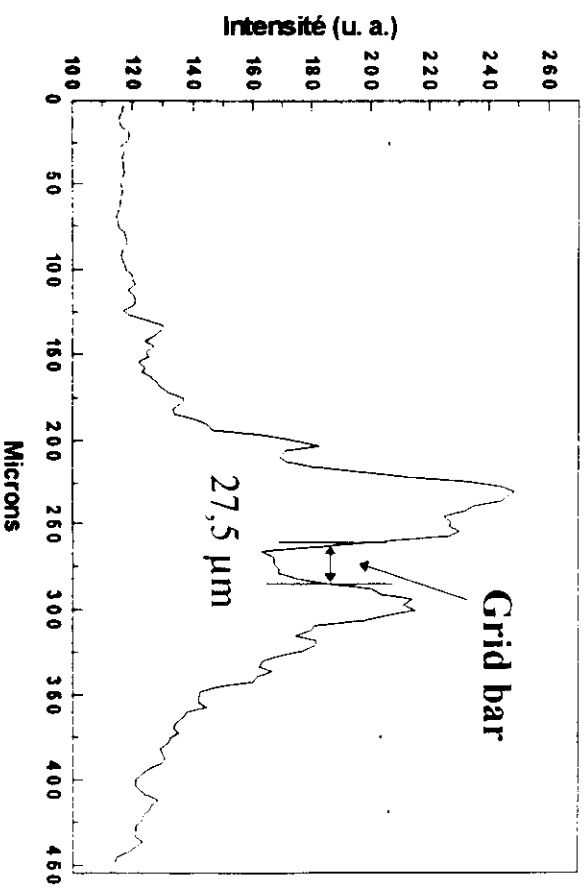
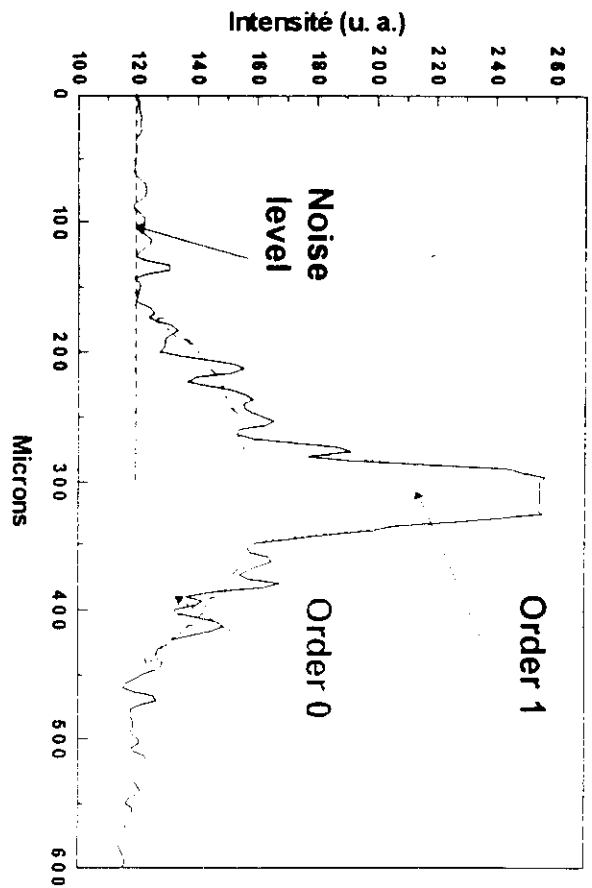
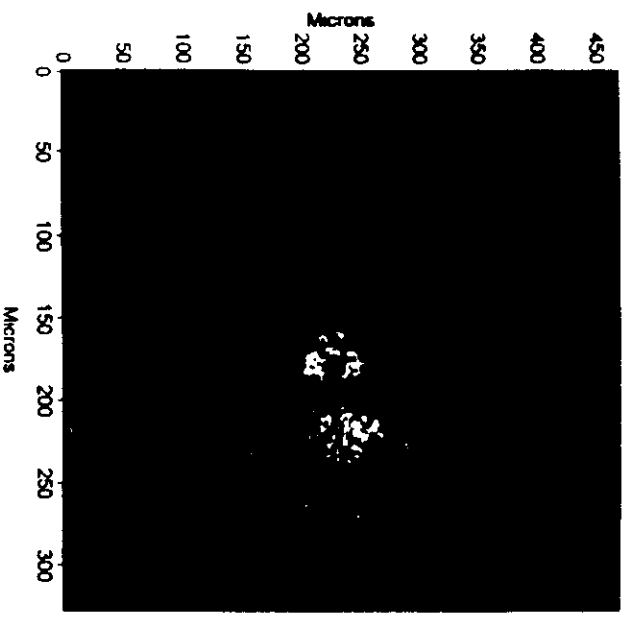
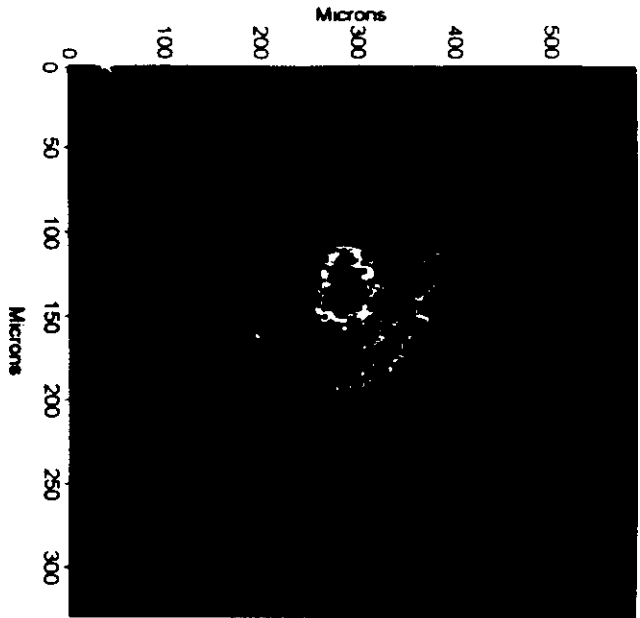
$$\delta_s = \frac{1.22 \lambda p}{2r_n}$$
$$= \frac{1.22 \times (7.725 \cdot 10^{-10}) \times 0.05}{2 \times 170 \cdot 10^{-6}}$$
$$\delta_s = 0.15 \mu\text{m}$$
$$\delta_i = G \cdot \delta_s \quad \text{avec } G = 5$$
$$\delta_i = 0.75 \mu\text{m}$$

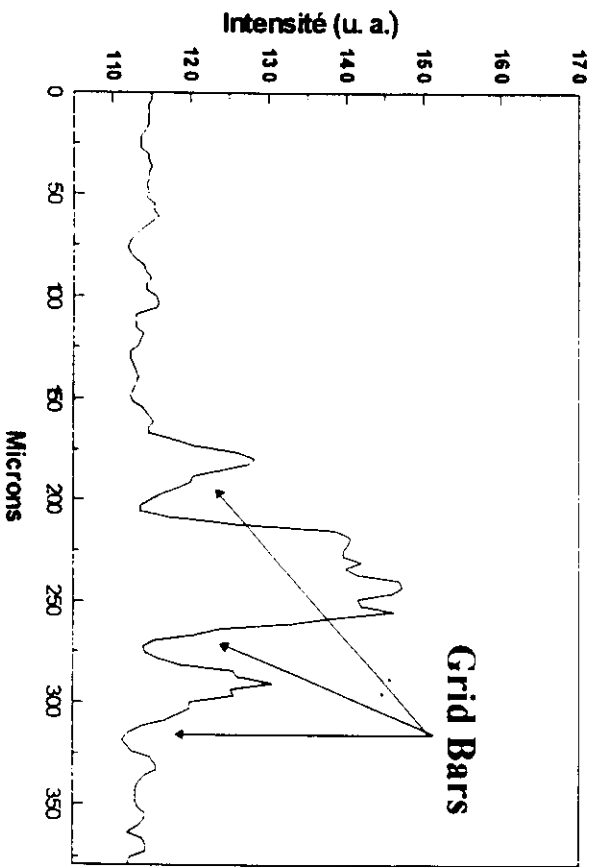
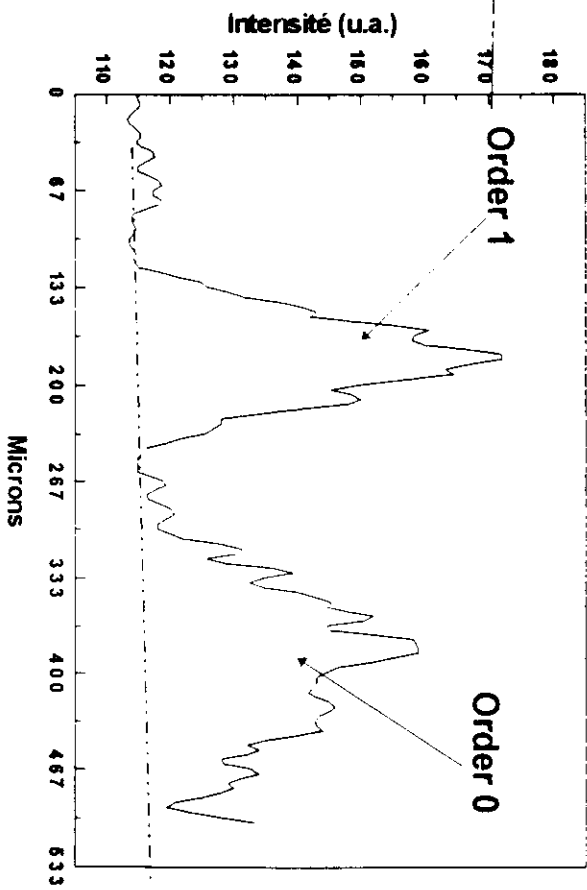
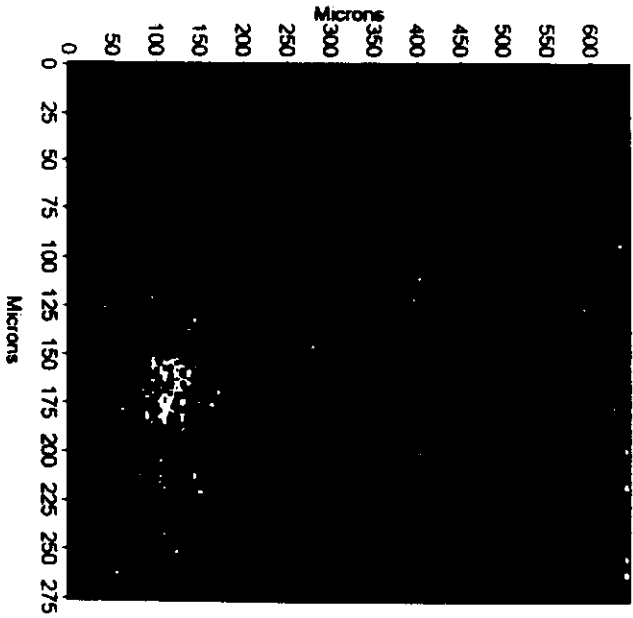
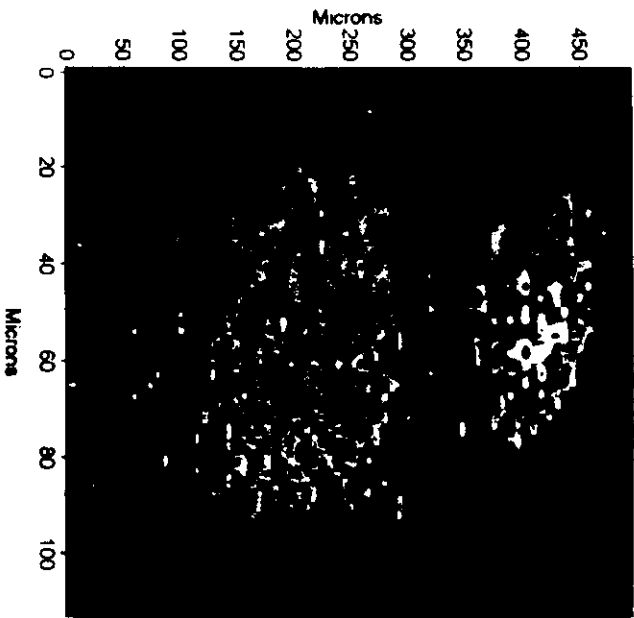
Matrice
CCD

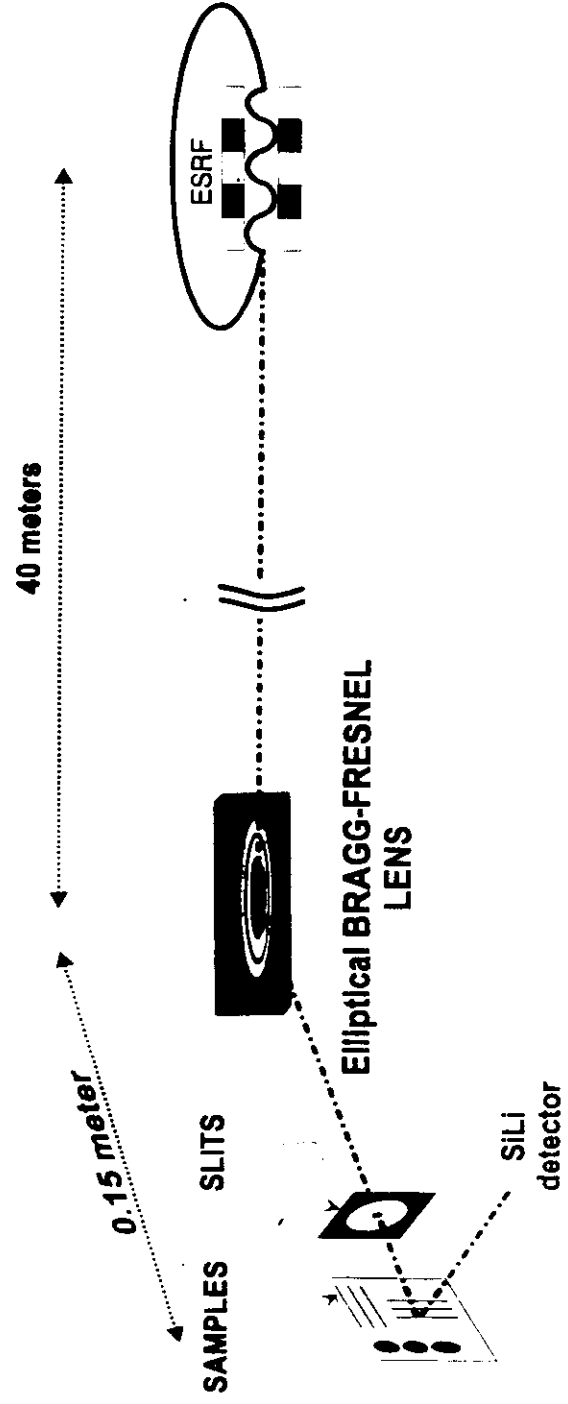
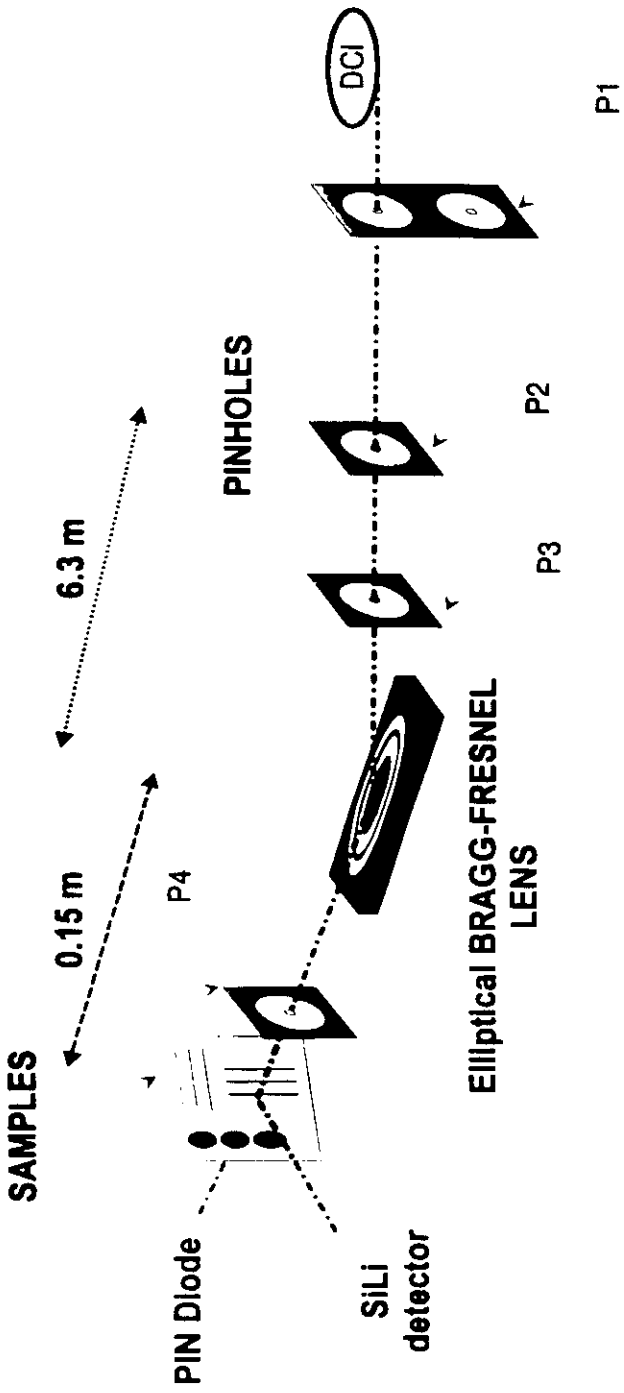


Material	Period : d_{∞} (Å)	γ	Number of bilayers
W / C	32	0,31	65

	Off-axis lens	Elliptical lens
Wavelength / Energy	7,725 Å / 1605 eV	7,725 Å / 1605 eV
Size	174,2 x 1166,1 μm	167,5 x 1094 μm
Number of grooves	de 175 à 350	100
Focal distance	4,2 cm	4,5 cm



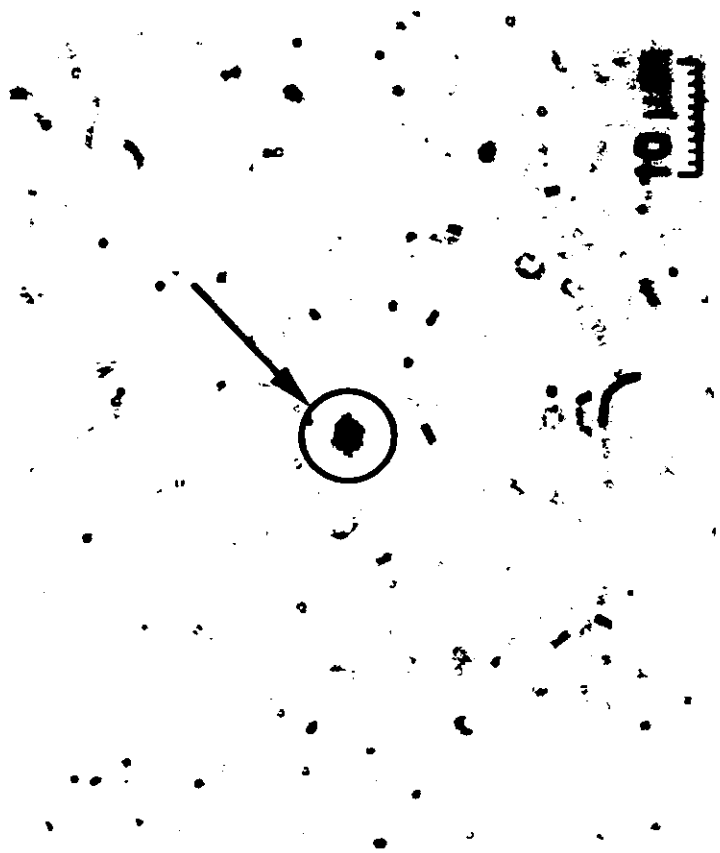






Multilayer characteristics : W/C $d= 32.5 \text{ \AA}$ 65 bilayers

**Lens characteristics : Size $60\mu\text{m} \times 2.48 \text{ mm}$
Last zone width $0.25 \times 10.7 \mu\text{m}$
F= 15 cm**



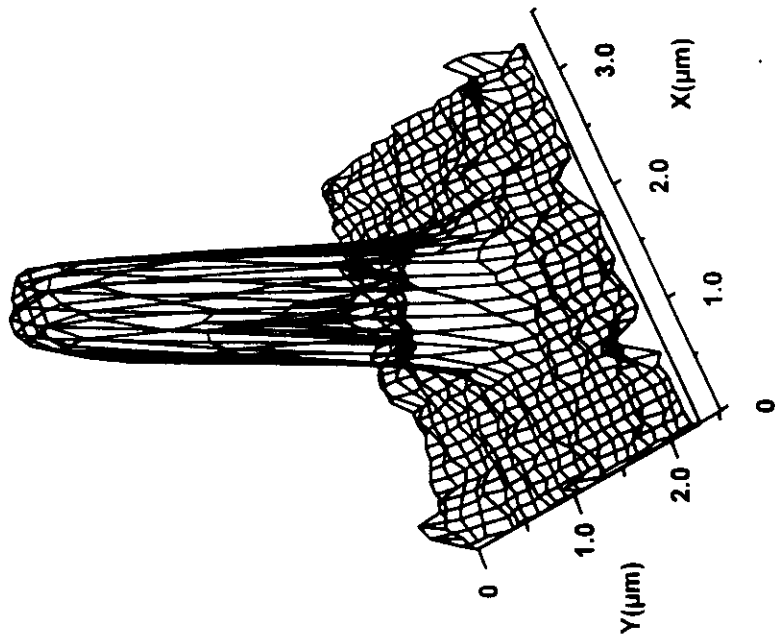
Storage ring DCI Beamline D15A

Energy : 12,4 keV

Intensity in the focal spot : $\sim 710^5$ phot/sec

Spatial resolution : $1 \times 1 \mu\text{m}$

Entrance pinhole : $50 \mu\text{m}$

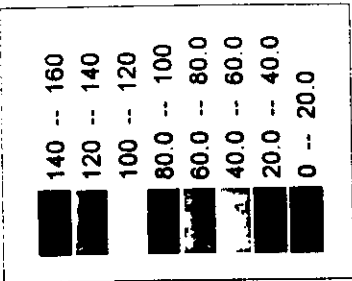
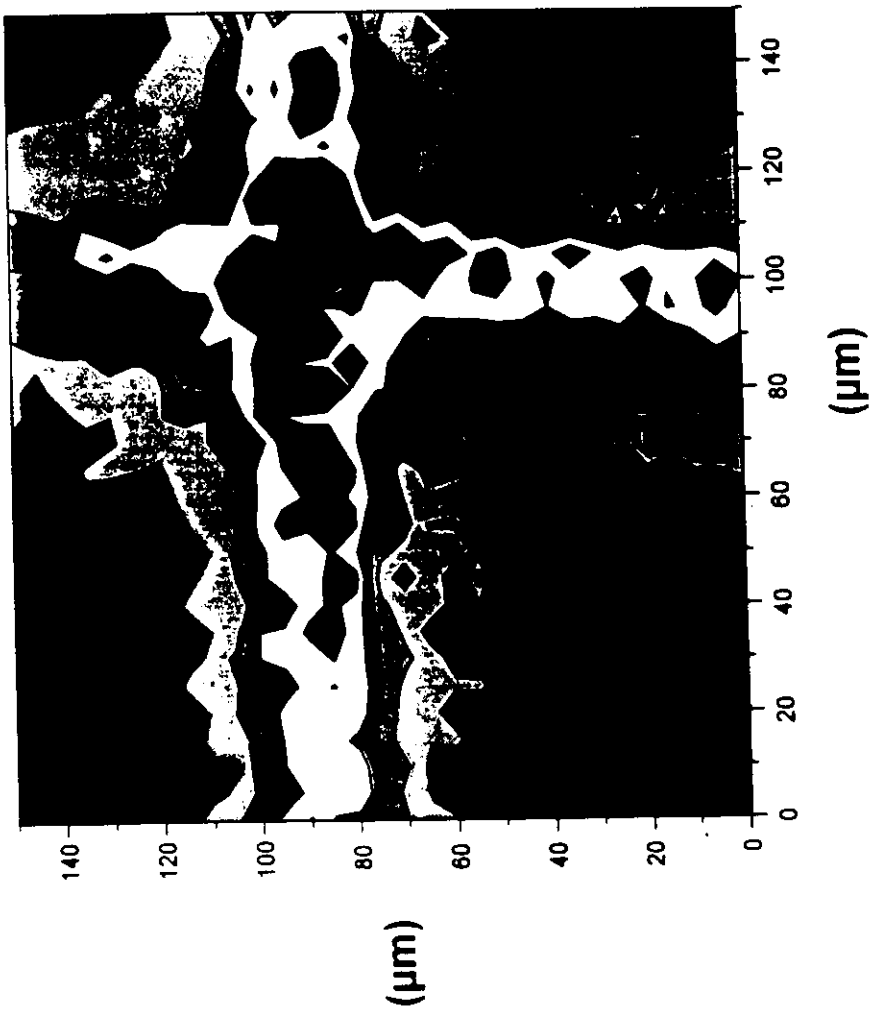


Storage ring ESRF Beamline Troika undulator

Energy : 11.8 keV

Intensity in the focal spot : $\sim 710^9$ phot/sec

Spatial resolution : $2.3 \times 5 \mu\text{m}$ (v x h)



Multilayer
E= 12.5 keV
W/C
d=32.5 A
65 bilayers

Lens Characteristics
60 μm X 2.48 mm (SIZE)
0.25 μm x 10.7 μm (Zone width)
F=15 cm

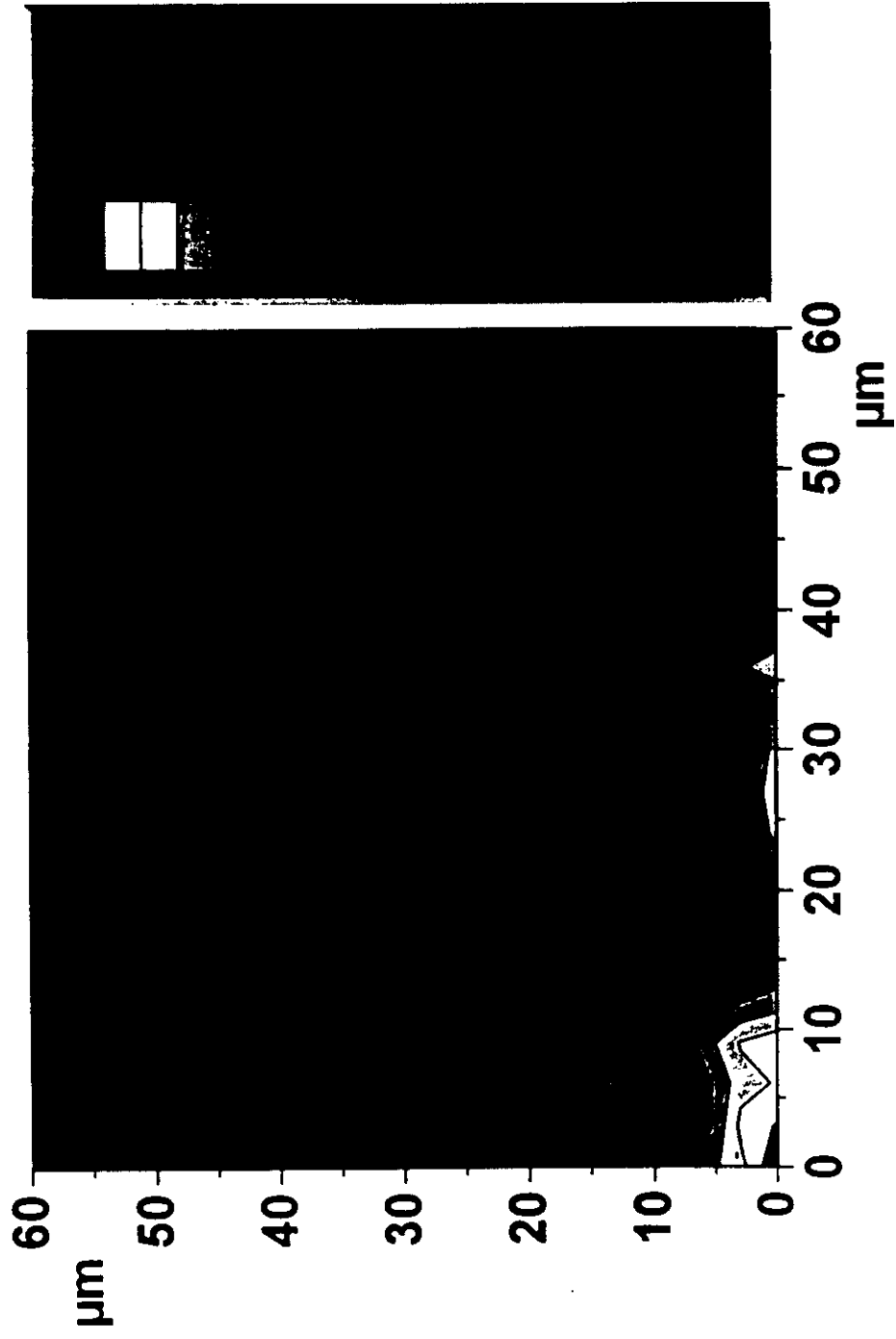
Micrométéorites from Antarctica

· C. Engrand & M. Morette

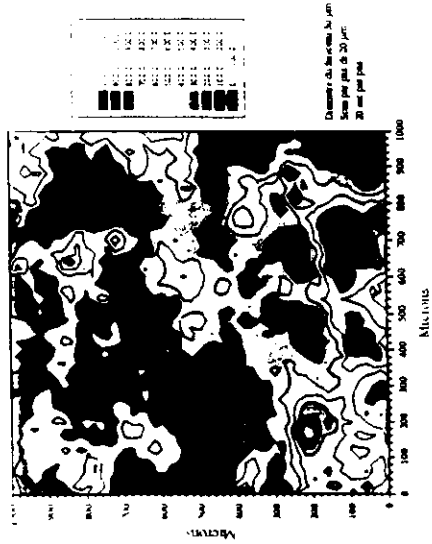
CSNSM-Orsay

· Microsonde on DCI

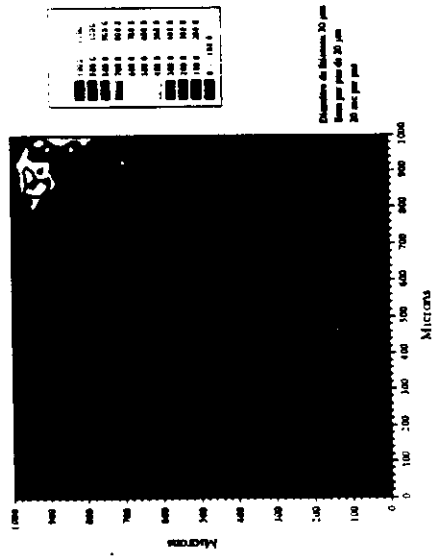
Iron K lines



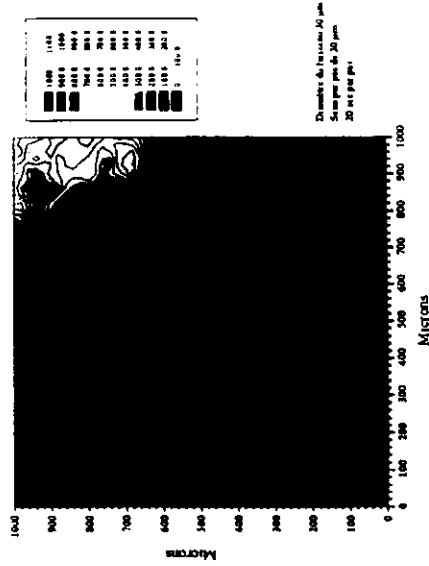
Cartographie du fer
P28-16



Cartographie du zinc
P28-16



Cartographie du plomb
P28-16



Cartographie de Mn
P28-16

